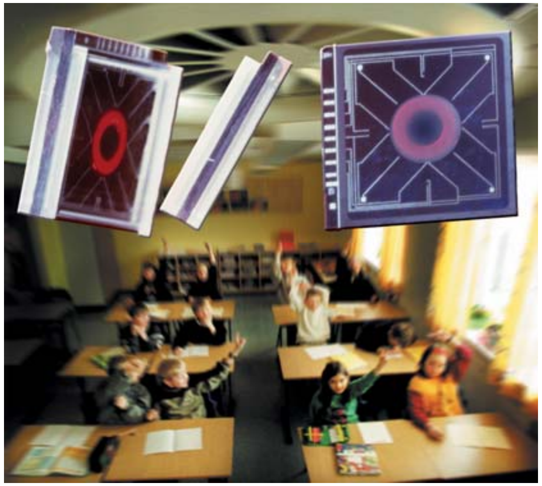
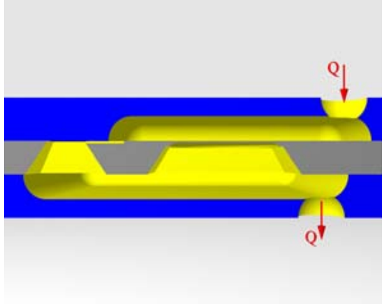
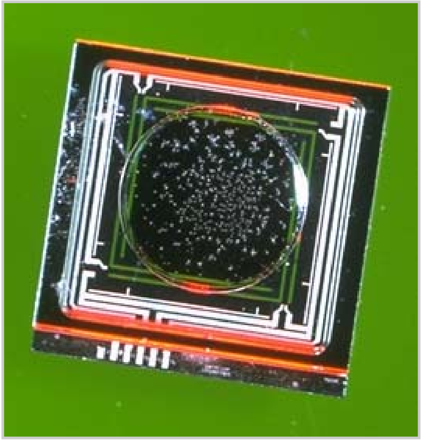
Fys4230
Mikro- og nanosystem modellering og design

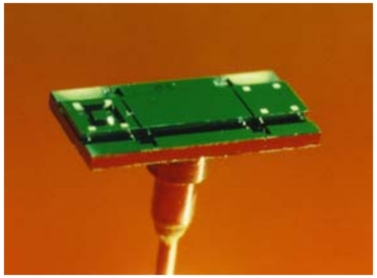
10 studiepoeng høsten 2006

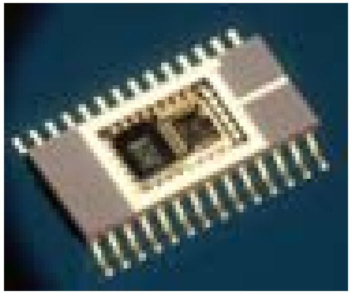




Foreleser Liv Furuberg
Seniorforsker
SINTEF Informasjon og kommunikasjonsteknologi







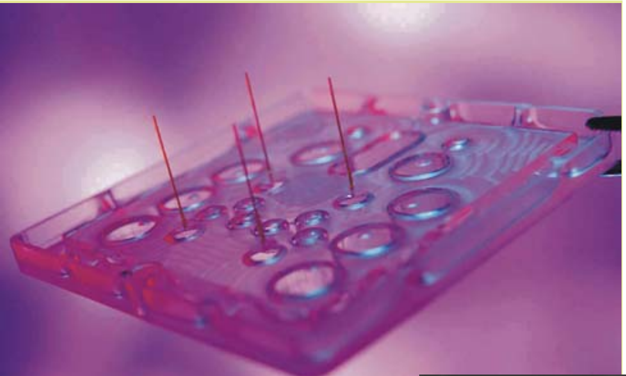
web page with all course information

- http://www.uio.no/studier/emner/matnat/fys/FYS4230/h06/

- Messages, keep yourself updated!
  - Example: next week lecture will take place in MiNaLab, Gaustadbekkdalen
- Powerpoint presentations from lectures
- Exercises
- 3 compulsory exercises, deadlines

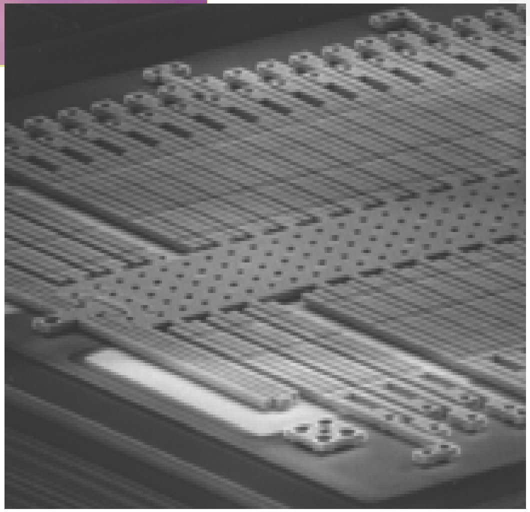
Course contents, 4 main “cases”:

1) Micro fabrication
2) Design of lithographic masks
3) Physics governing behaviour of microsystems
4) Modelling of behaviour of microsystems

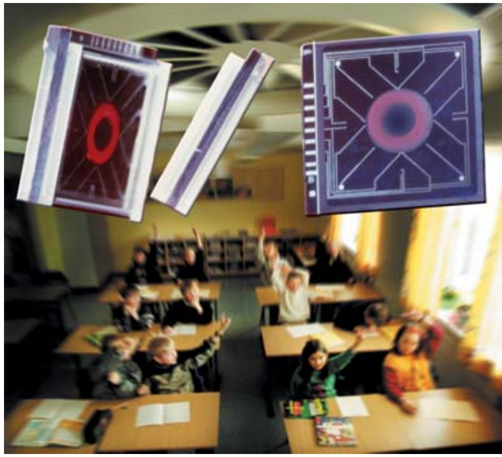


Lab-on-a-chip

Projector

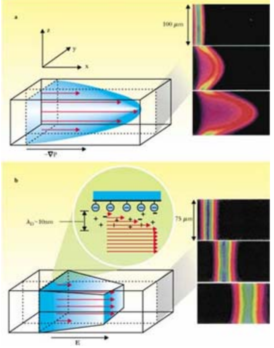


Accelerometer

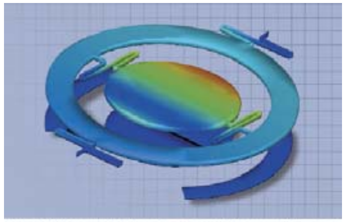


Pressure sensor

Fluid dynamics

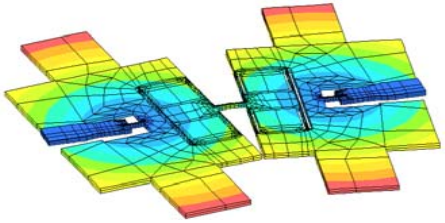


Multiphysics



Analysis of a MEMS mirror illustrates the relative displacement of its components. You can also analyze modal frequency, residual stress, maximum stress, electrostatic force of electrodes, beam diffraction, and crosstalk between multiple mirrors in an array.

Structural mechanics



Electronics

Signal processing

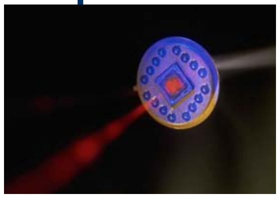
Electromagnetism

Chemistry

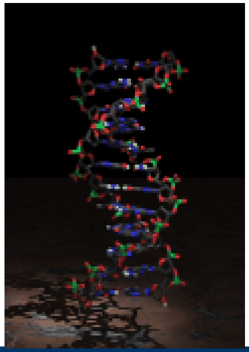
Challenge:

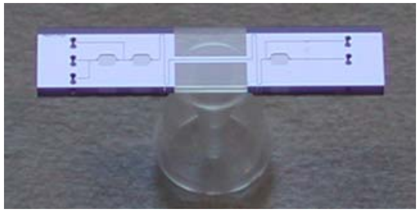
Design functional elements that can be manufactured by microtechnology

Optics



Biotechnology



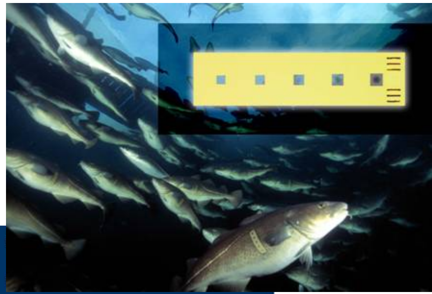


Capillary flow

Surface physics

Functional thin films

Material science

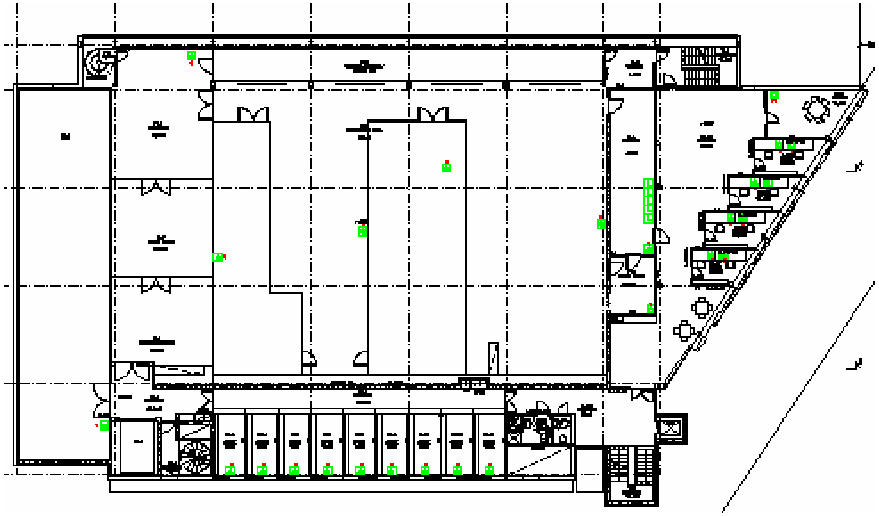


MiNaLab i Oslo

- Mikro- og Nanoteknologilaboratoriet I Gaustadbekkdalen
- MiNaLab

- Mikrosystemer = TVERRFAGLIGHET!

MiNaLab



SINTEF:

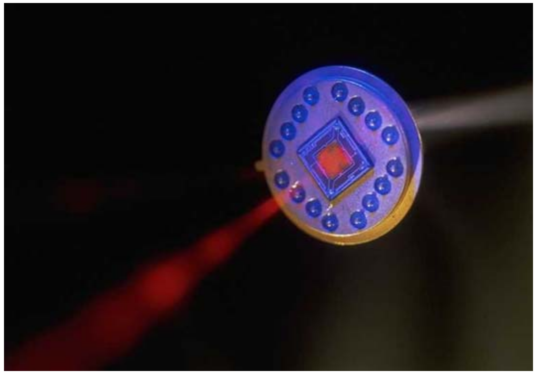
- Renromsareal: 800 m^2
- Microenvironments med klasse 10
- Ballroom: klasse 1000
- Produksjonslinje med årlig kapasitet opp til 8000 silisiumskiver

Universitetet i Oslo:

- Renromsareal 400 m^2

- Utstyr: NFR
- Bygget: SINTEF + NFR

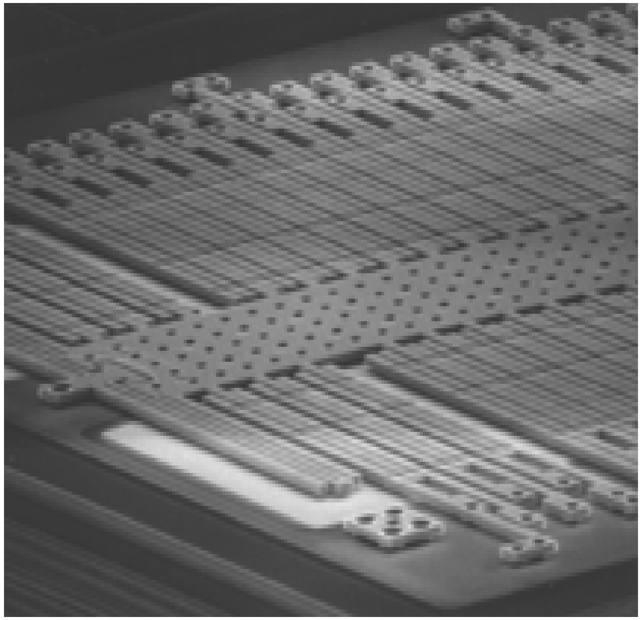
- **MEMS (Micro-Electro-Mechanical Systems)**
- **Microsystems**
- **Microtechnology**

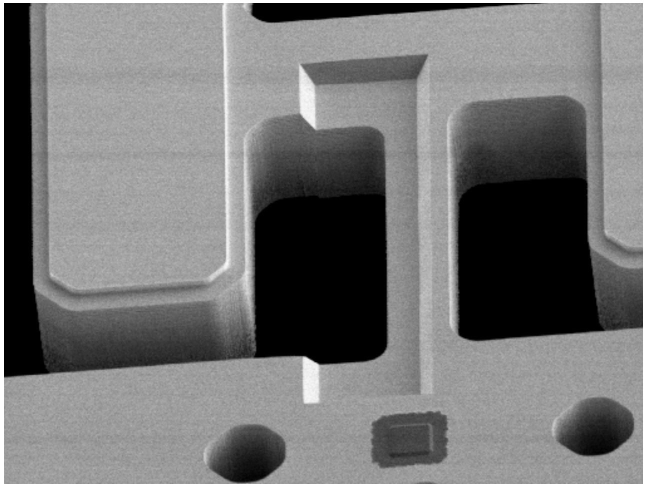


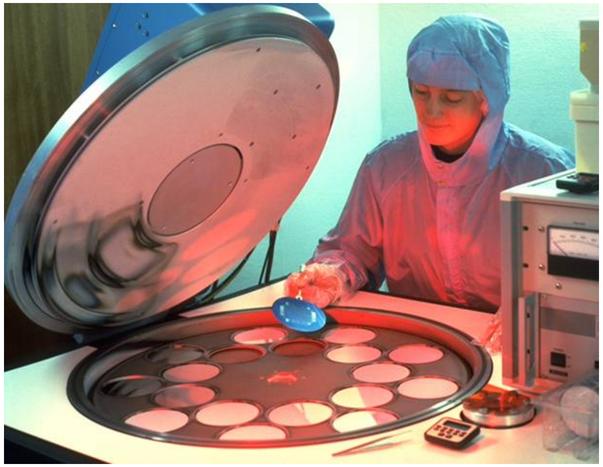
- Sensors and actuators
- The functional element is of micrometer scale
- Made from silicon, quartz or polymer
- Integrated with electronic circuits
- Produced using integrated circuit fabrication technologies

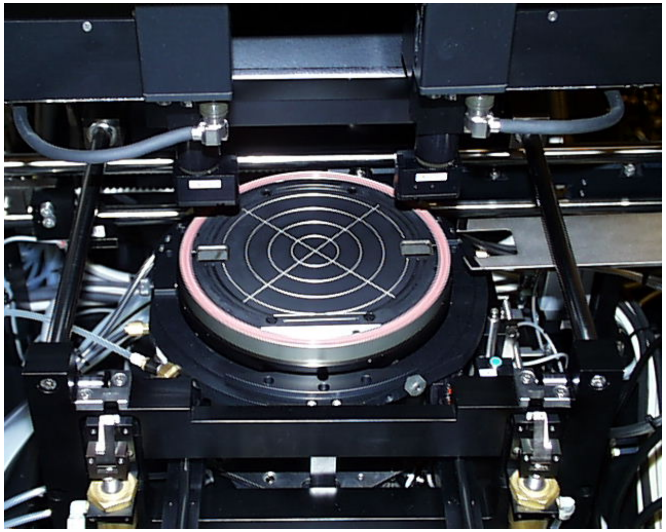
Micromachining

- Top – down manufacturing
- 3D structures
- Lithography defines areas to be etched away
- Bonding of several wafers
- Thin films





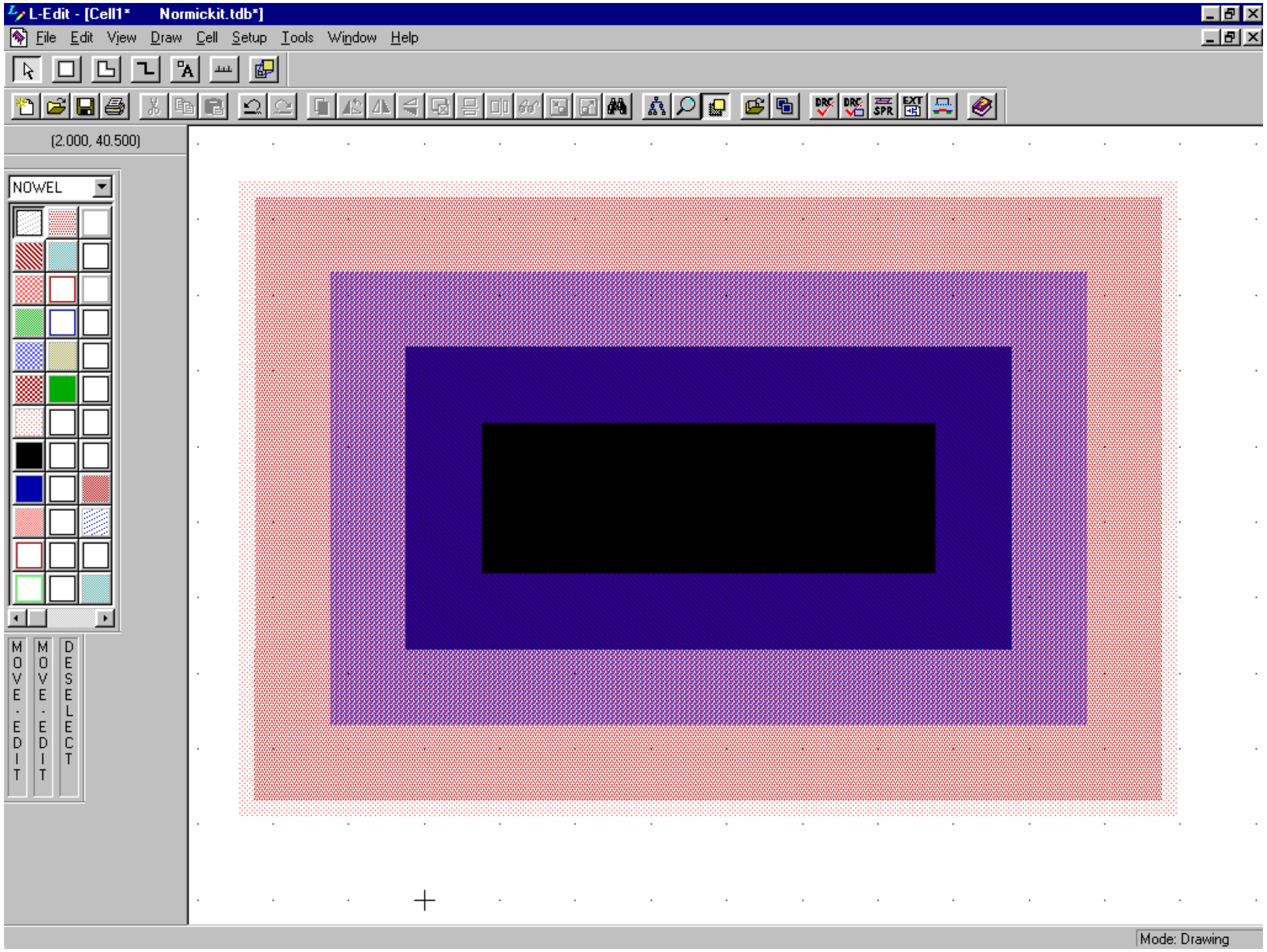


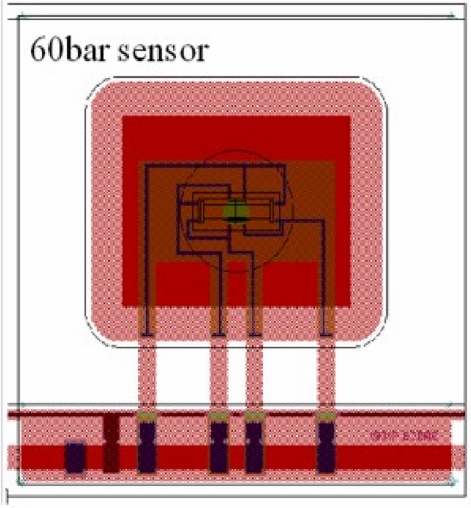


Micromachining equipment, SINTEF

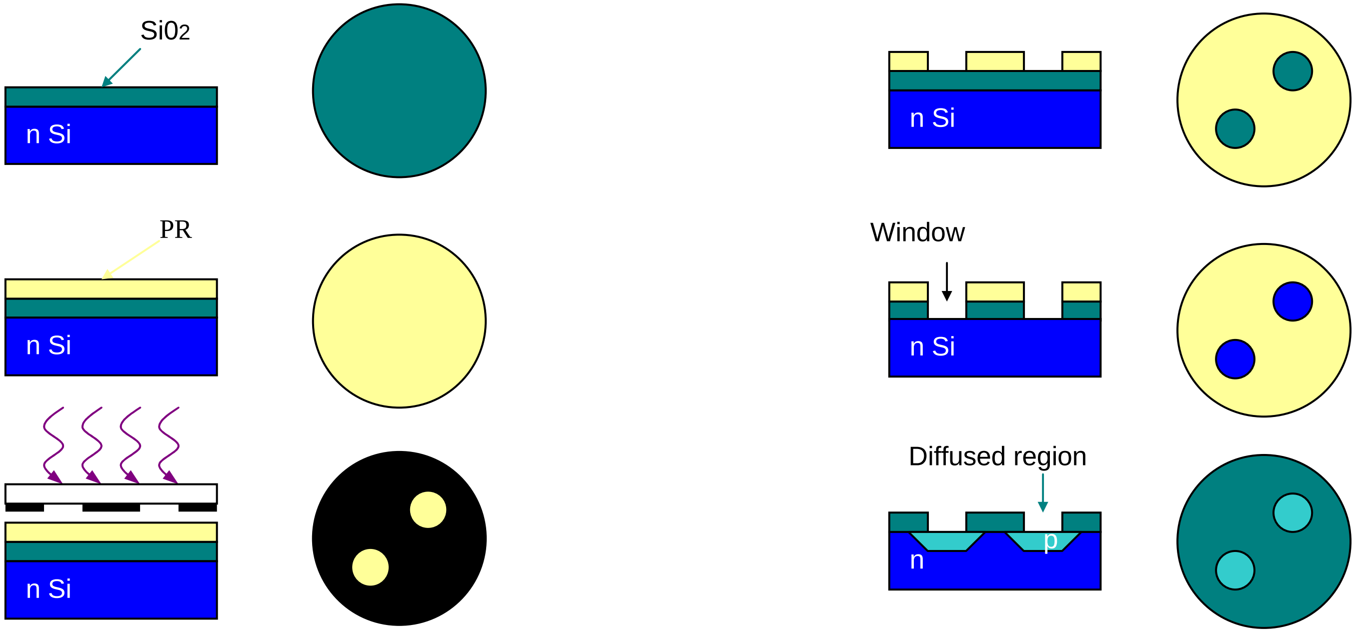
- Photolithography
- Furnaces for diffusion and oxidation
- ICP PECVD (deposition)
- Deep reactive ion etch
- Wet etch of silicon
- “Quick and dirty room”
- Silicon/glass wafer bonding
- Dicing
- Measurement lab + SEM

Layout of lithographic masks

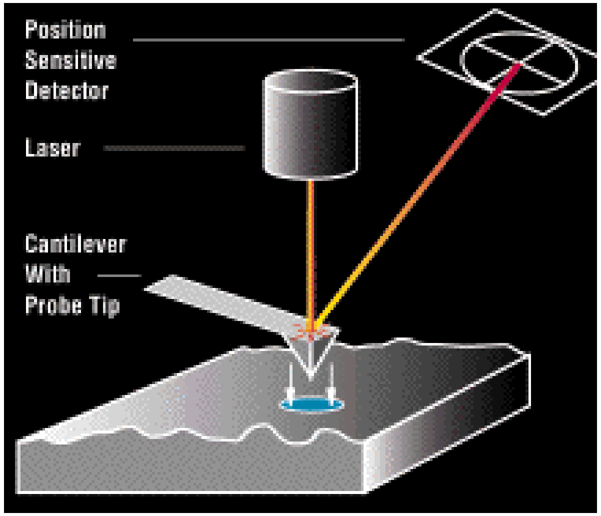


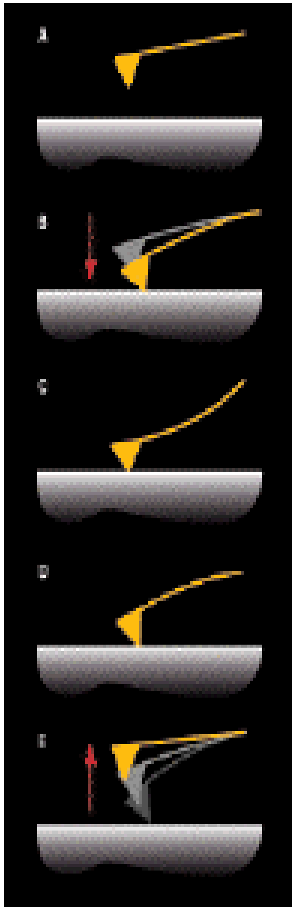


Fotolitografi
Mønsteroverføring fra maske til resistfilm på silisiumskive



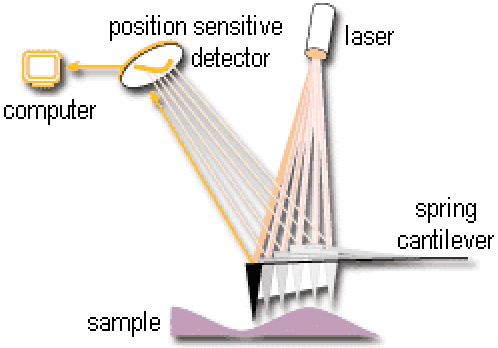
Beam example: Atomic Force Microscope





- Measures force between tip of cantilever and object
- E.g. forces from surface, weight of molecule
- Size of cantilever:
  - 100-500 μm long
  - 0.5-5 μm thick

- How to measure forces?
  - Deflection of beam due to force can be measured by reflection of light
  - Mechanical stress in beam is related to force and deflection and can be measured with piezoresistors



Translating biomolecular recognition into nanomechanics
Science 288, 2000

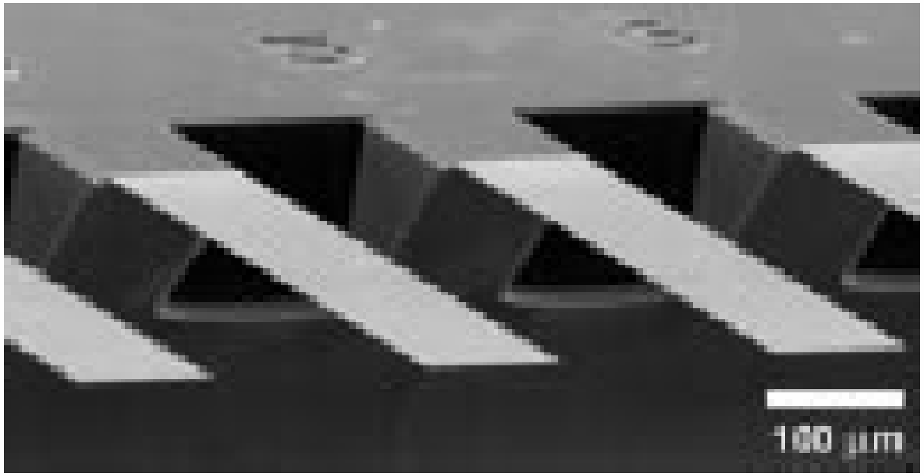


Fig. 1. Scanning electron micrograph of a section of a microfabricated silicon cantilever array (eight cantilevers, each 1 µm thick, 500 µm long, and 100 µm wide, with a pitch of 250 µm, spring constant 0.02 N m^{-1}; Micro- and Nanomechanics Group, IBM Zurich Research Laboratory, Switzerland).

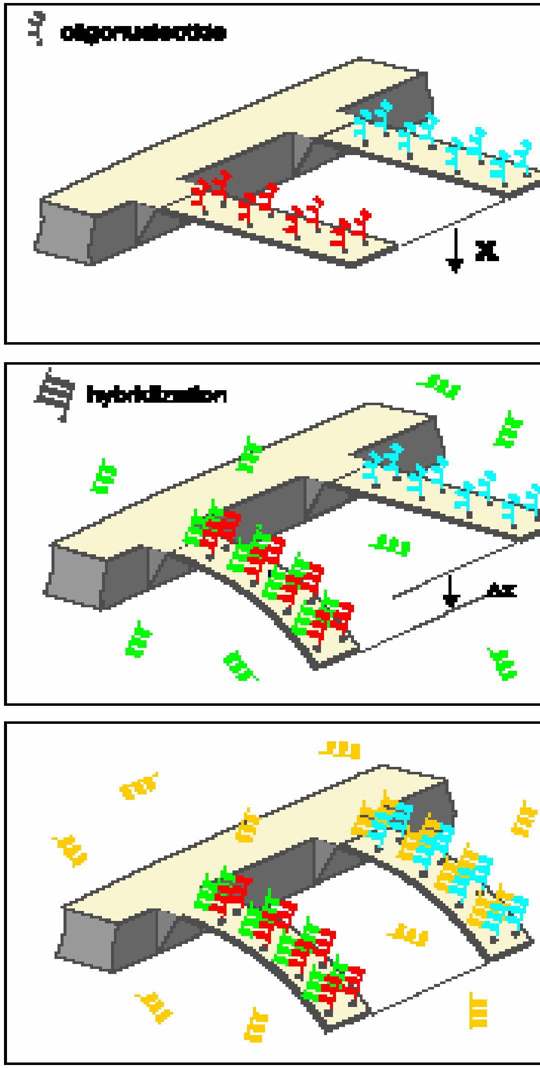
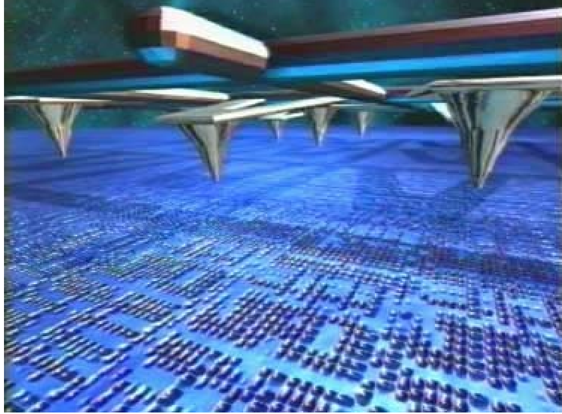


Fig. 2. Scheme illustrating the hybridiza
experiment. Each cantilever is functionalize
one side with a different oligonucleotide
sequence (red or blue). (A) The differe
signal is set to zero. (B) After injection of
first complementary oligonucleotide (gre
hybridization occurs on the cantilever that
vides the matching sequence (red), increa
the differential signal Δx. (C) Injection of
second complementary oligonucleotide (
low) causes the cantilever functionalized
the second oligonucleotide (blue) to bend.

Bulk silicon micromachining

Millipede, IBM Zurich



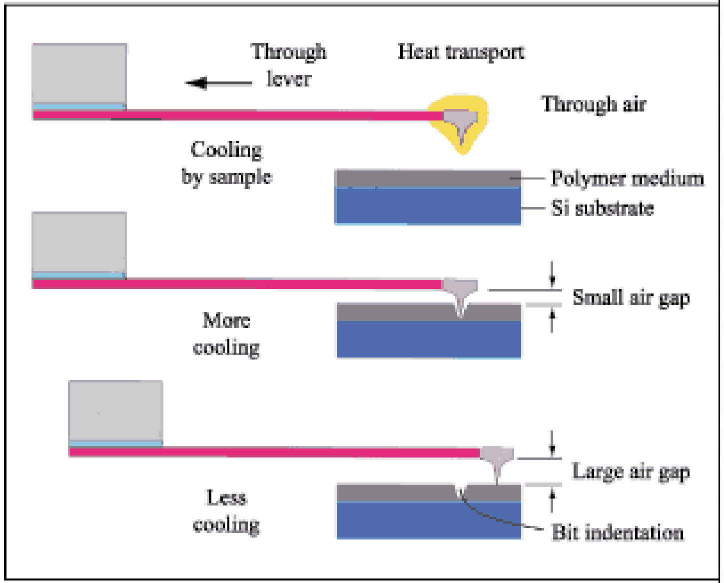


Figure 4

Principle of AFM thermal sensing. The heater cantilever is continuously heated by a dc power supply while it is being scanned and the heater resistivity measured. Adapted from [17(a)], with permission; © 1999 IEEE.

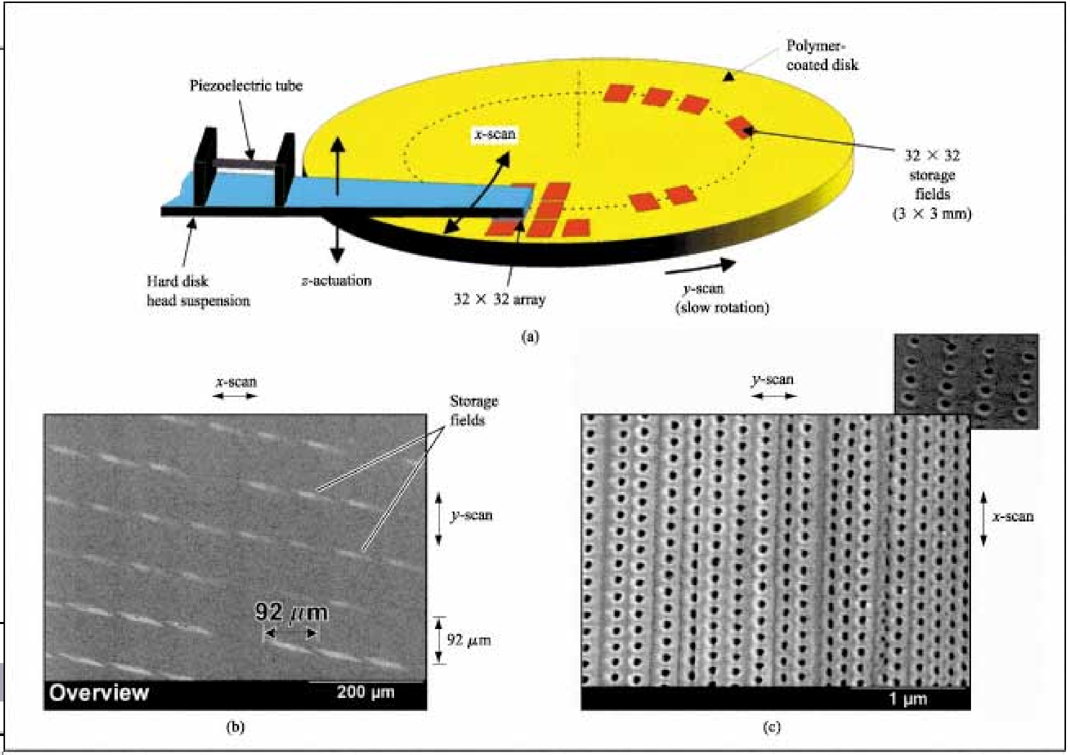


Figure 14

(a) Modified hard disk Millipede approach for array-chip scanning and displacement, and writing results; (b) SEM image of many storage fields; (c) magnified bit indentations in 100-nm-thick PMMA medium, equivalent to a storage density of 70–100 Gb/in.^{2} Note that the *x*/*y* scan directions are interchanged between (b) and (c).

Capasitive surface comb-accelerometer

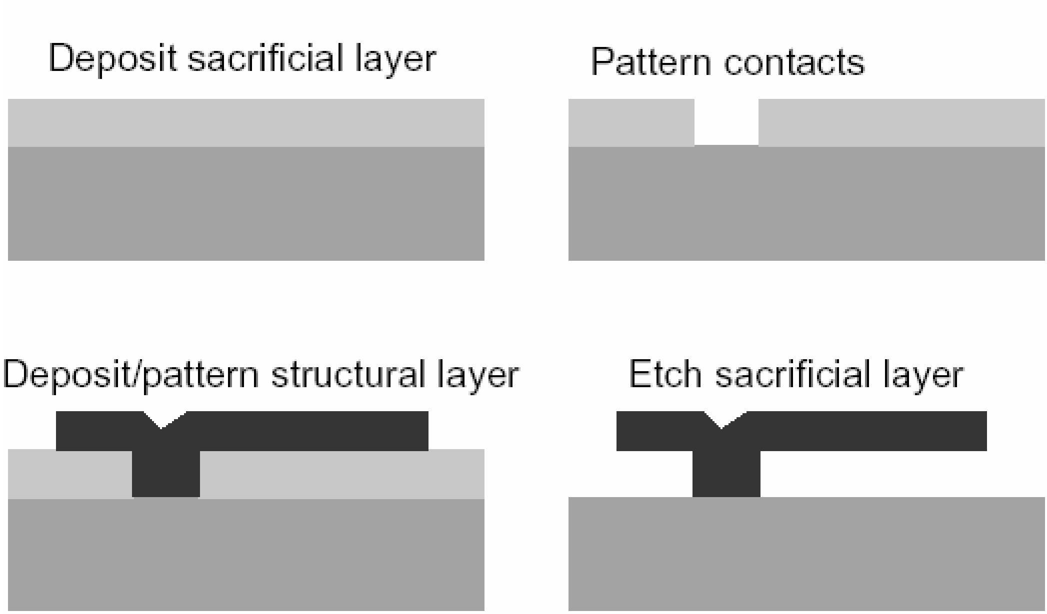
- Polysilicon
Surface micromachining
- Cronos: PolyMUMPs
(multi-project-wafer process)

Design of:

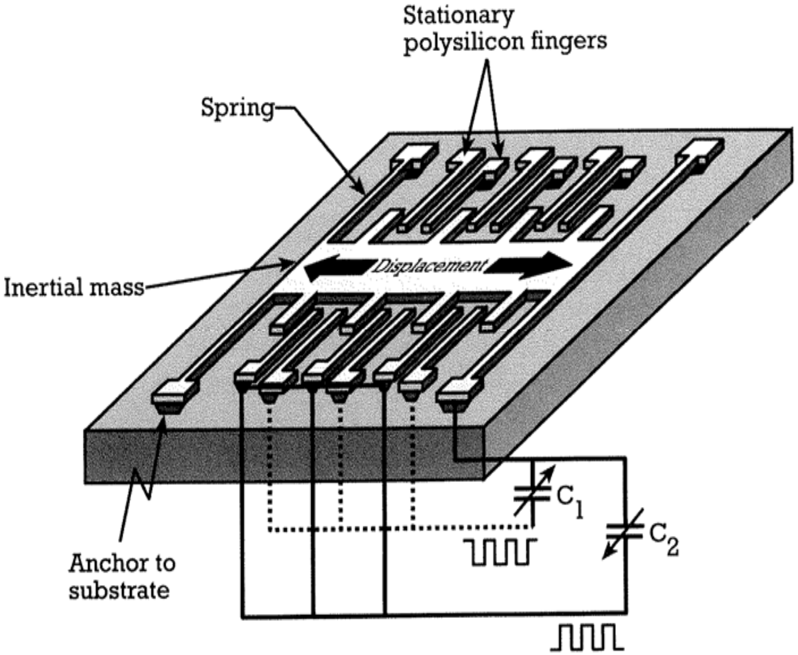
- Low-g accelerometer (5g)
- Capacitive read-out: collaboration with microelectronics

Self-test

Analog Devices



A Capacitive Accelerometer



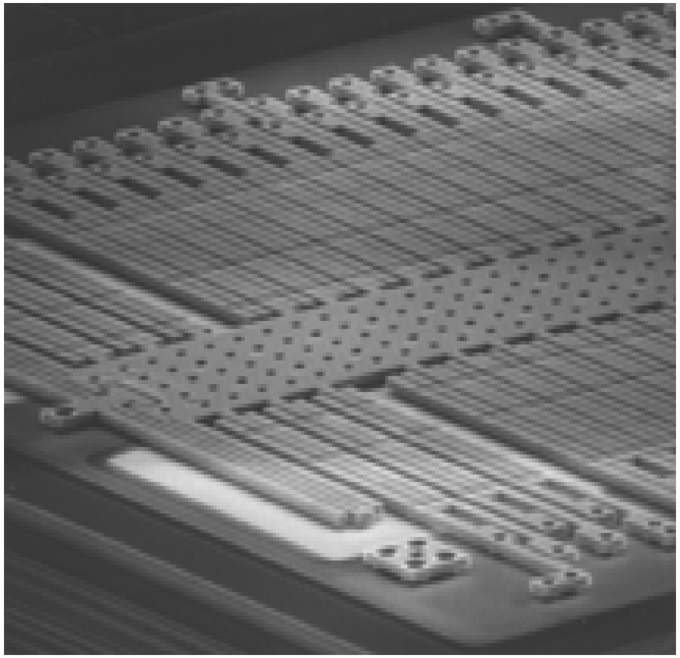
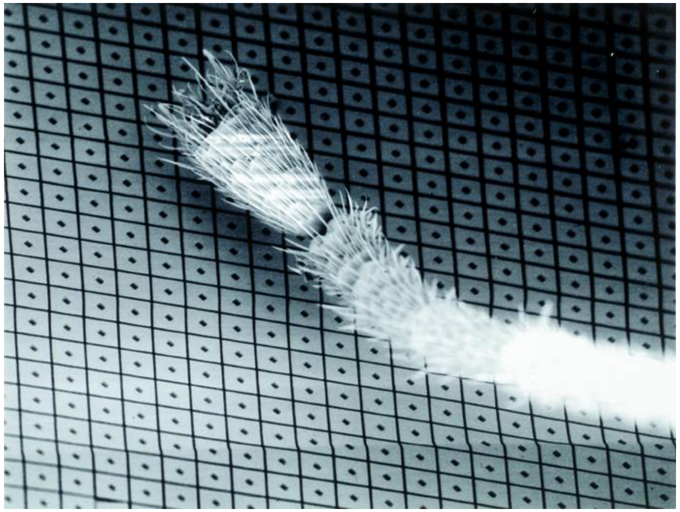
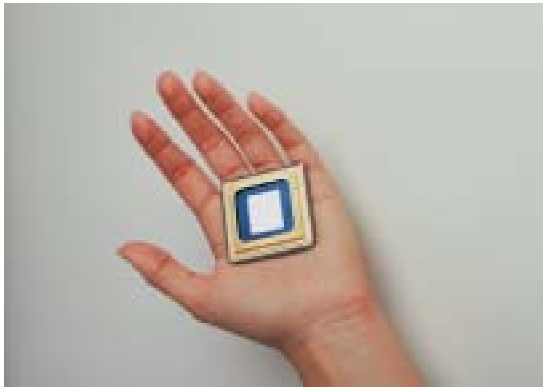


Image projector with micromachined mirrors Digital Light Processing, Texas Instruments

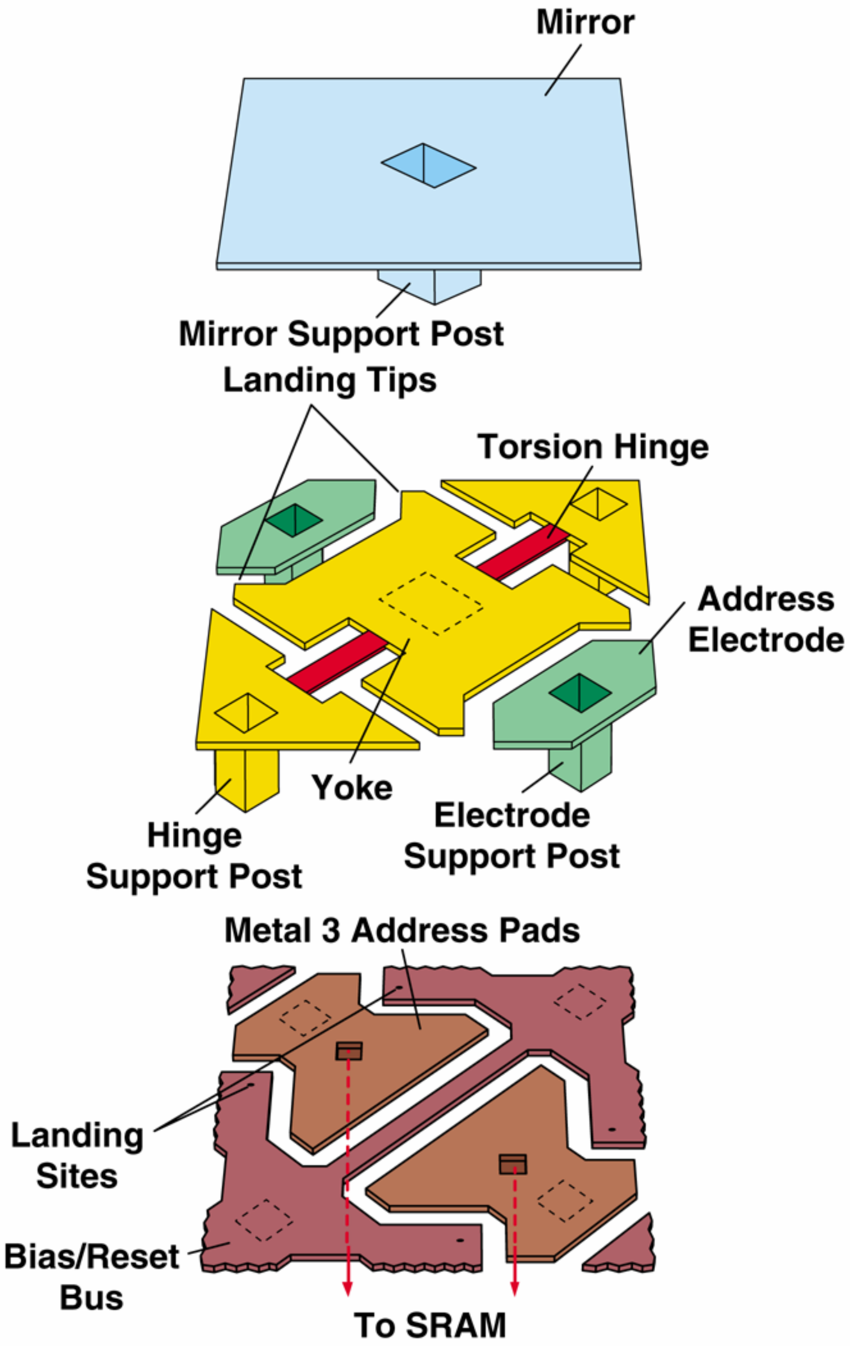


- Aluminium micromirrors fabricated on the surface of a silicon wafer with an integrated circuit
- Mirrors are individually controlled
- Size of mirror: 16µm x 16µm
- Mirrors separated by 1µm
- One chip: 1280x1024 mirrors (1 310 720 mirrors)

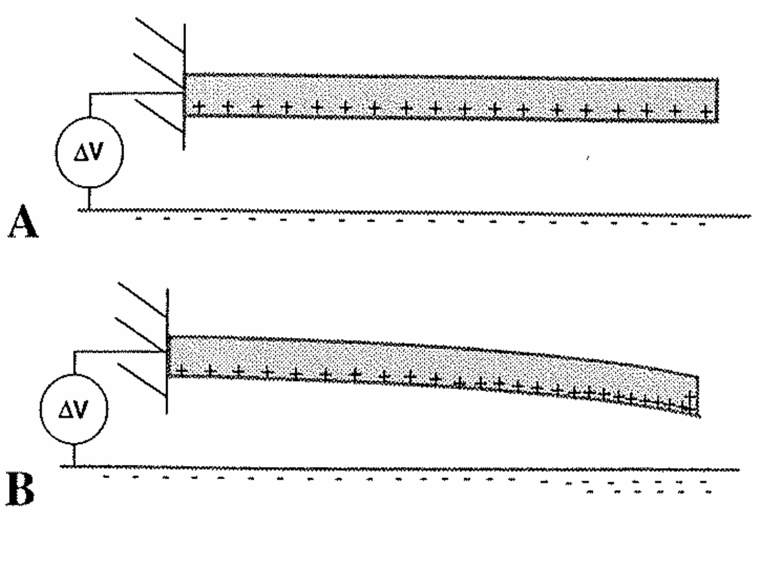


One micromirror

- Actuated by electrostatic forces: apply a potential difference between mirror and electrode
- Elastic torsion forces oppose the tilt



Electro-Mechanical behaviour



- Coupled electro-mechanical problem

Governing equations

- Electrostatic potential between electrodes solving the Laplace equation
- Elasticity equation solved inside the beam

Solve

- Solve fully coupled systems of partial differential equations
- Alternately solve equations until equilibrium is reached

Surrounding fluid/gas

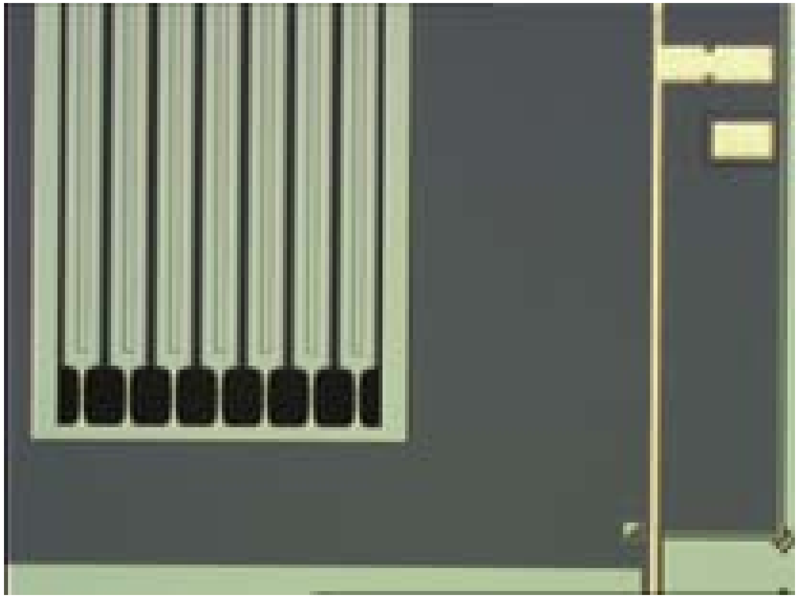
- Reynolds equation solved separately
- Viscous damping, film spring effect

Bulk-micromachined mirror

MultiMEMS
Your multifunctional MEMS service

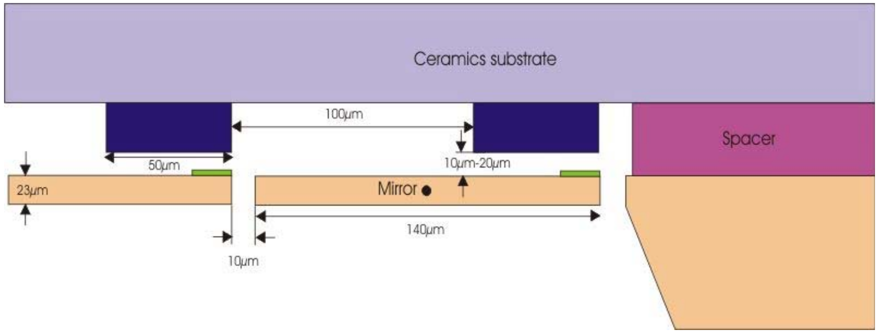
- Application: bar-code reader
- Electrostatic actuation
- Mirrors tilts
- Packaging: Tick film on ceramics (Microcomponent)

- Modellering: Multiphysics
  - Elasticity
  - Elektrostatics
  - Fluidics

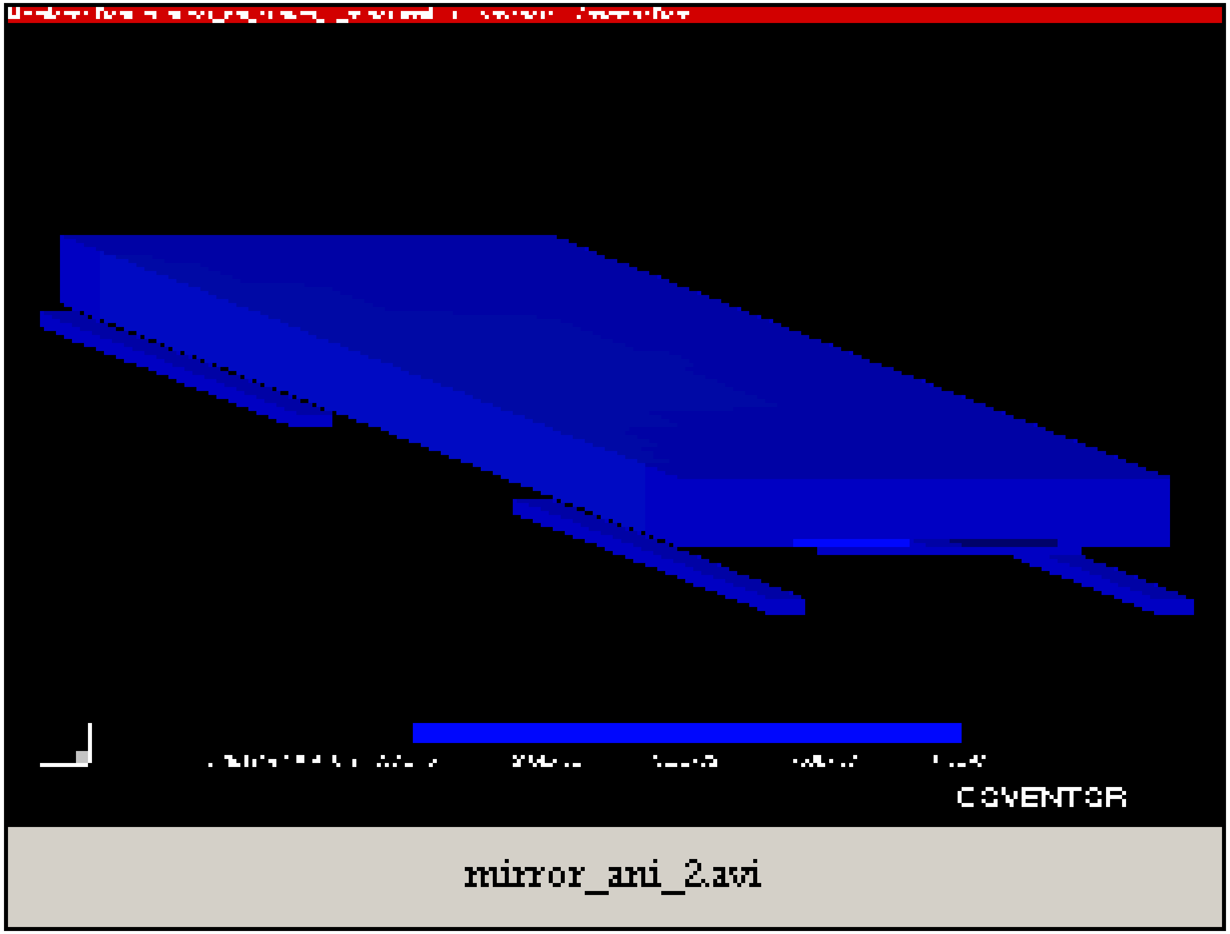


Parallel plate condensator ≈

$$F = -\frac{A\varepsilon\varepsilon_0}{2x^2}V^2$$



Coupled electrostatic-elastic simulation of mirror



Klaus Magnus Johansen, Oddvar Søråsen, Liv Furuberg, UiO

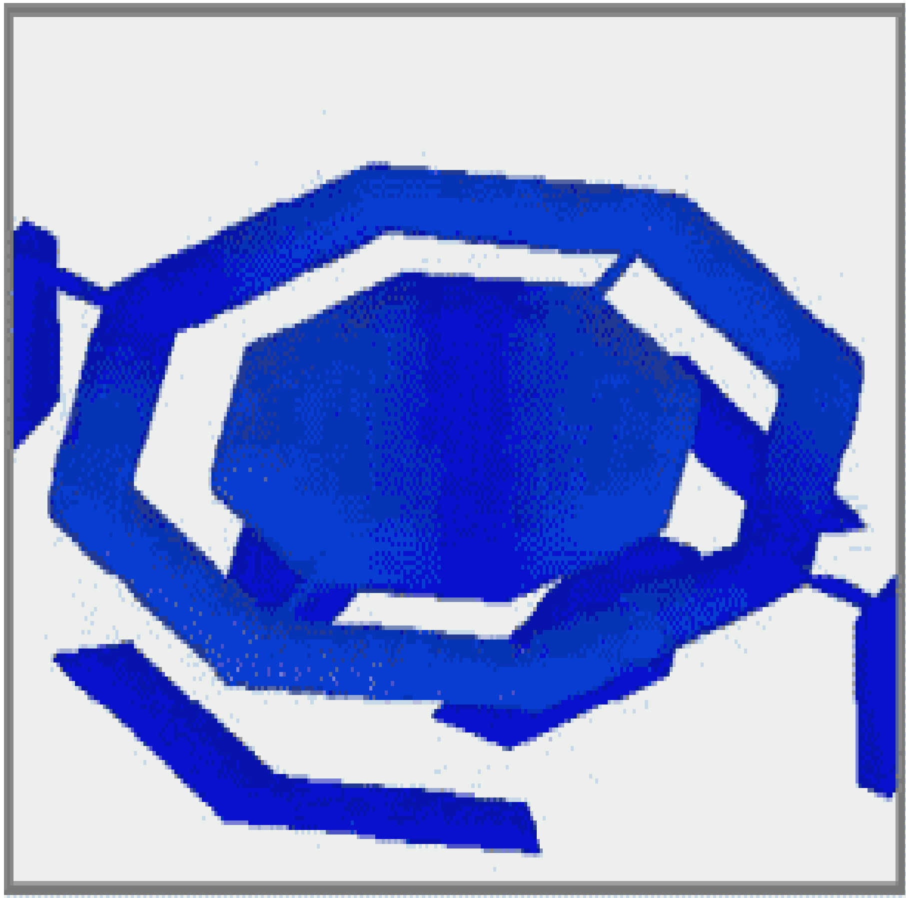
Mechanical and electrostatic equations

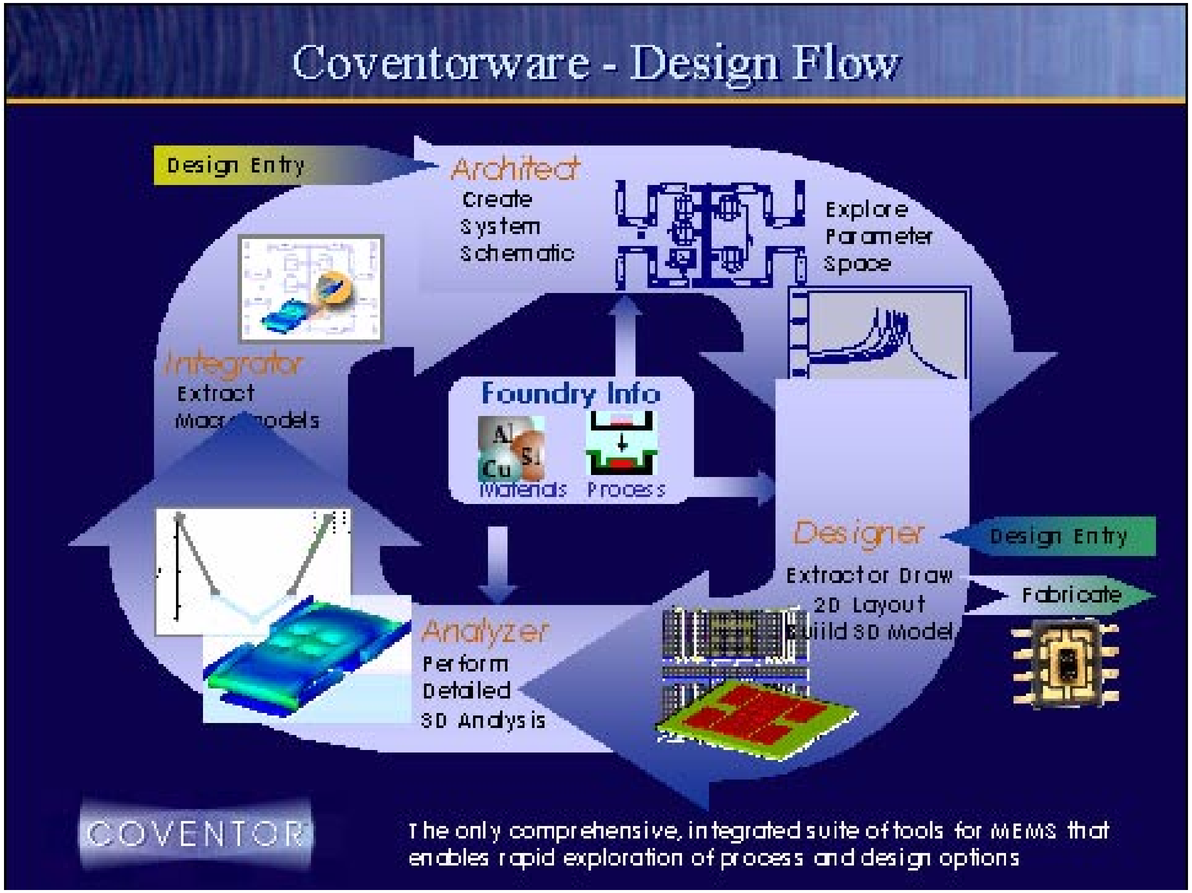
- Naviers equation for elastic forces: (isotropic version)

$$(\lambda+\mu)\nabla\nabla\cdot u+\mu\nabla^2 u=0$$

- Poisson equation for electrostatic field:

$$\nabla^2\Phi=-\frac{\rho}{\varepsilon}$$





Coventorware - Design Flow

Design Entry

Architect
Create System Schematic

Explore Parameter Space

Integrator
Extract Macromodels

Foundry Info
Materials
Process

Designer
Extract or Draw 2D Layout
Build 3D Model

Design Entry

Fabricate

Analyzer
Perform Detailed 3D Analysis

COVENTOR

The only comprehensive, integrated suite of tools for MEMS that enables rapid exploration of process and design options

Detailed modelling levels

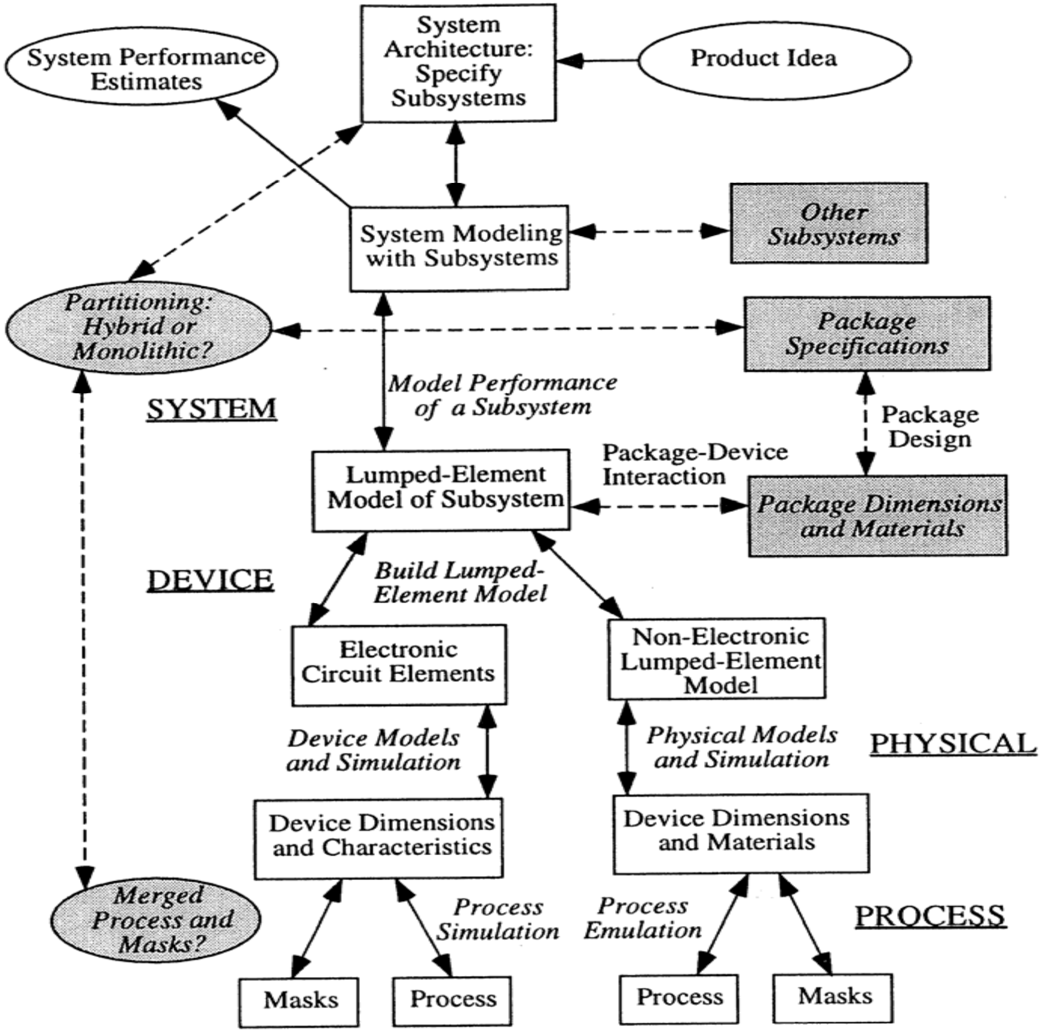
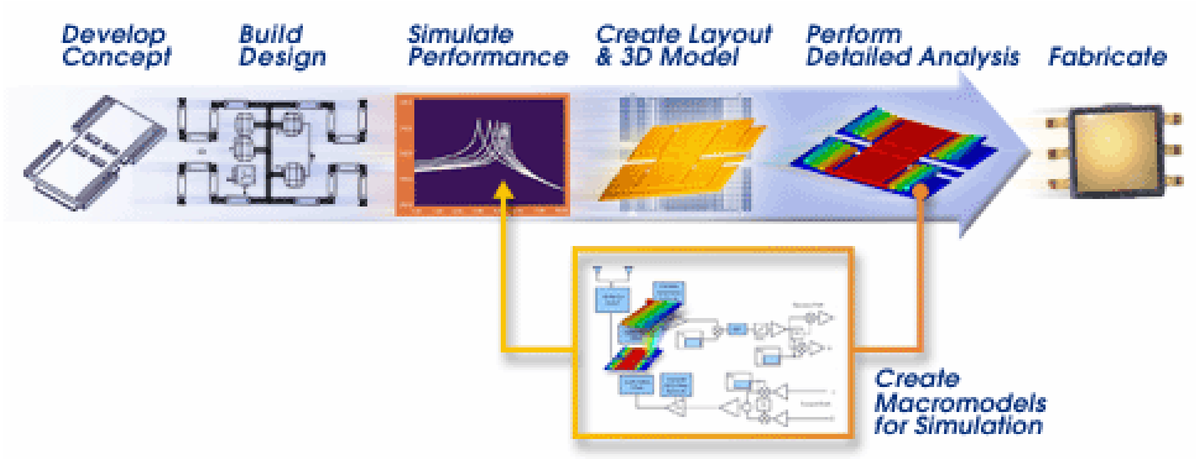
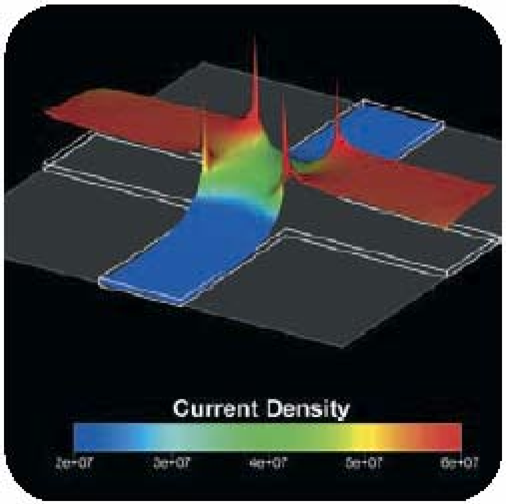


Figure 2.3. An expanded view of the "Modeling and Analysis" block of Fig. 2.1. The various modeling levels of Fig. 2.2 are indicated, and correspond to the entries in italics between the unshaded blocks. The shaded blocks are additional aspects of the design process not captured in Fig. 2.2.

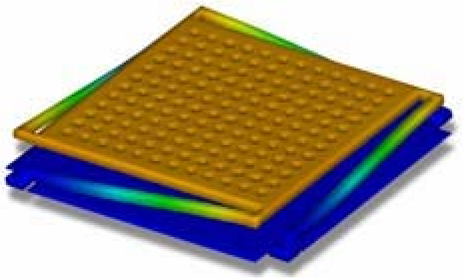
Coventorware ANALYZER

- Device modelling
- Continuum mechanics
- Electromagnetism
- Optics
- Piezoelectricity
- Piezoresistivity
- Fluidics



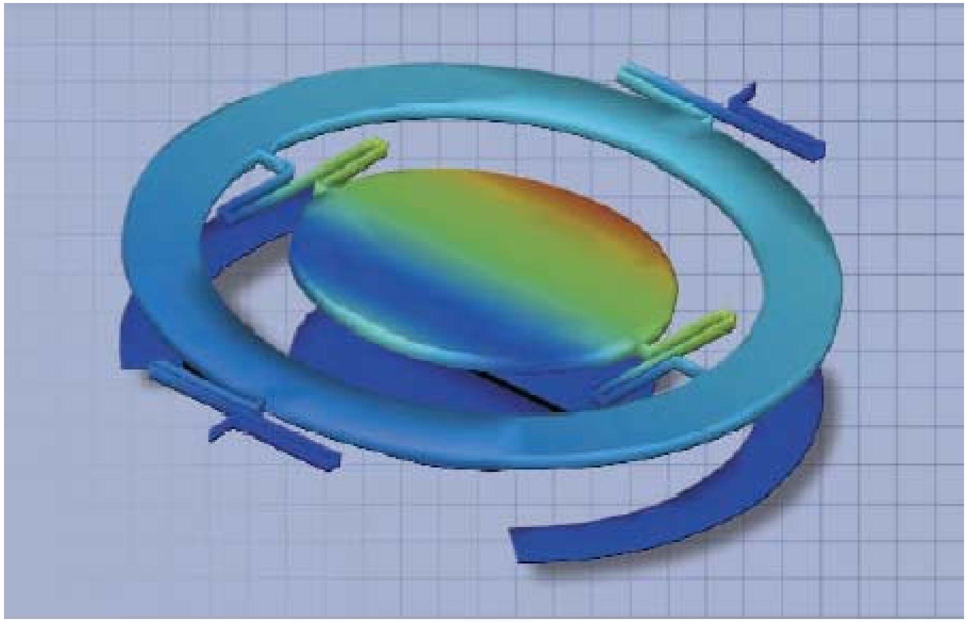


MemPZR analysis of a piezo-resistor cross



Coventorware Microsystem modelling and layout

- Process generation
- Mask layout
- **Device modelling**



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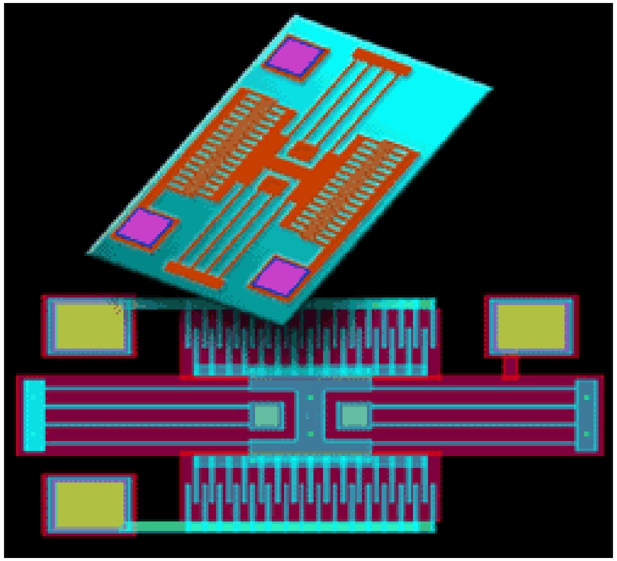
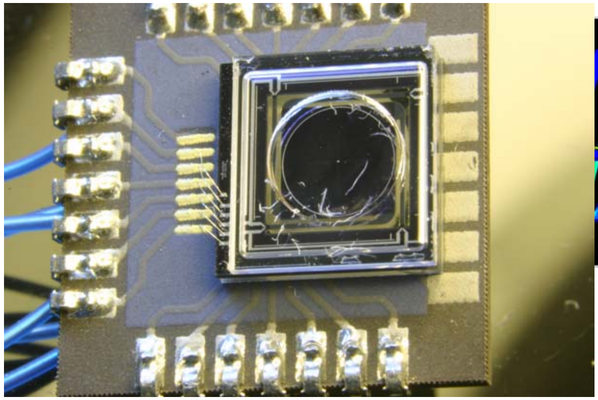
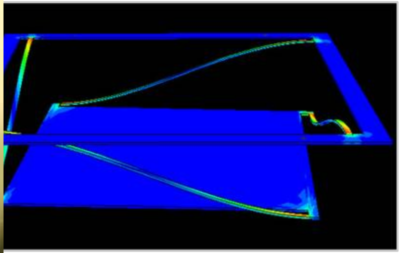


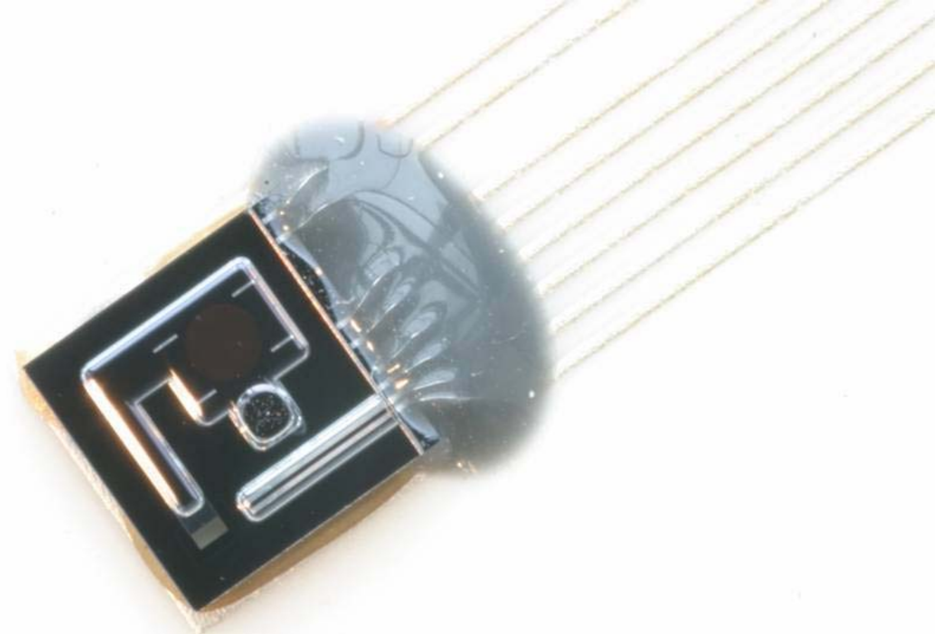
ist
information society technologies



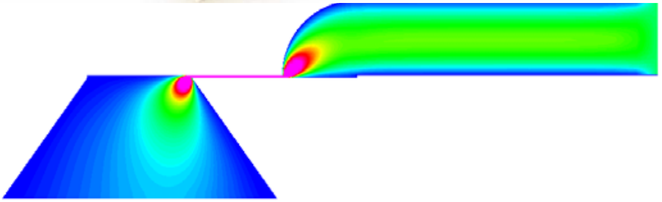


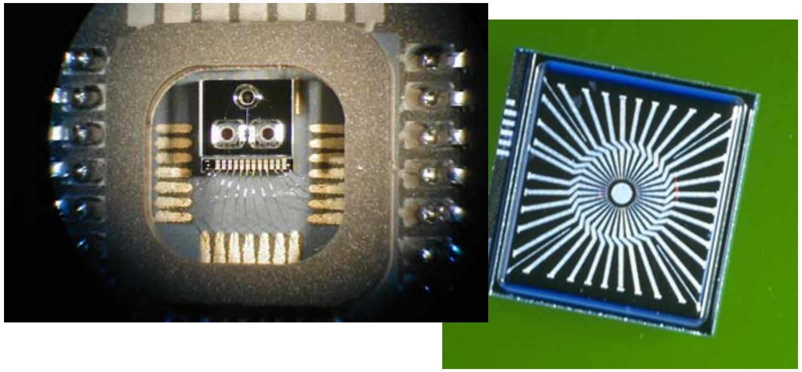
EUROPRACTICE

MultiMEMS
Your multifunctional MEMS service

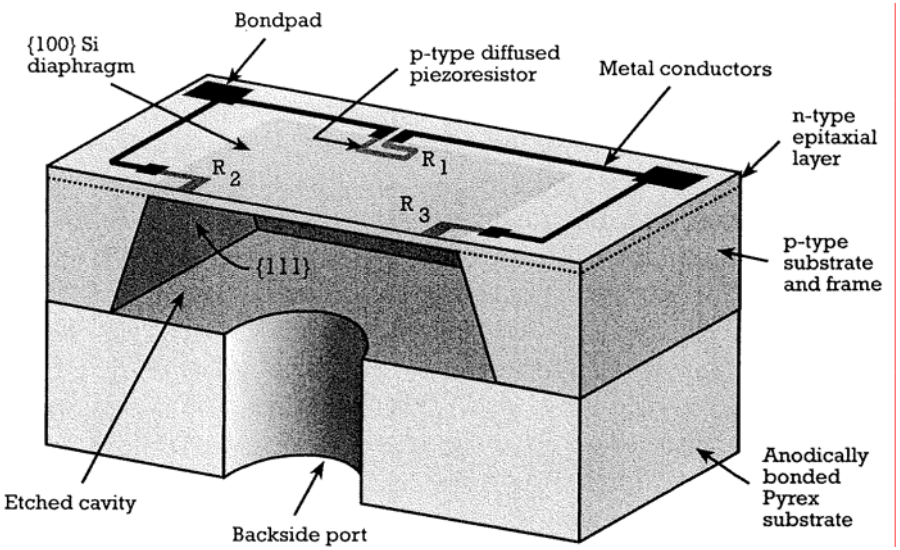


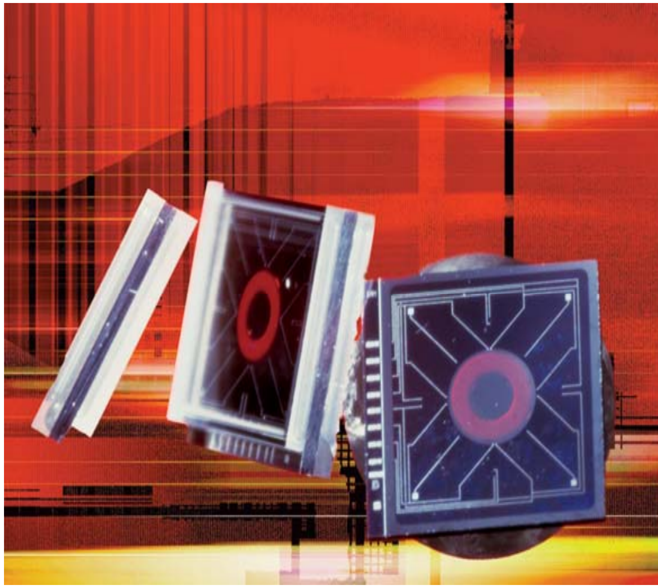
microBUILDER

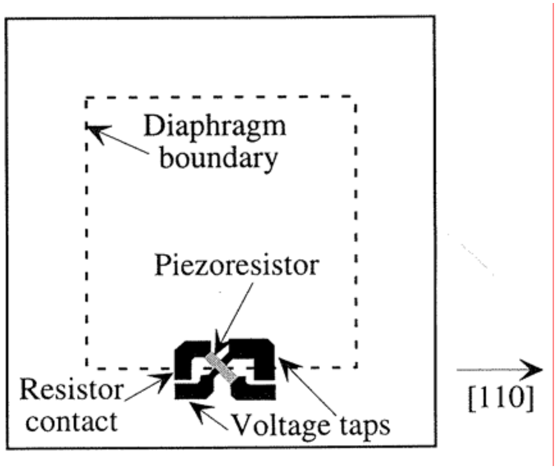




Piezoresistive pressure sensors







Mechanical modelling

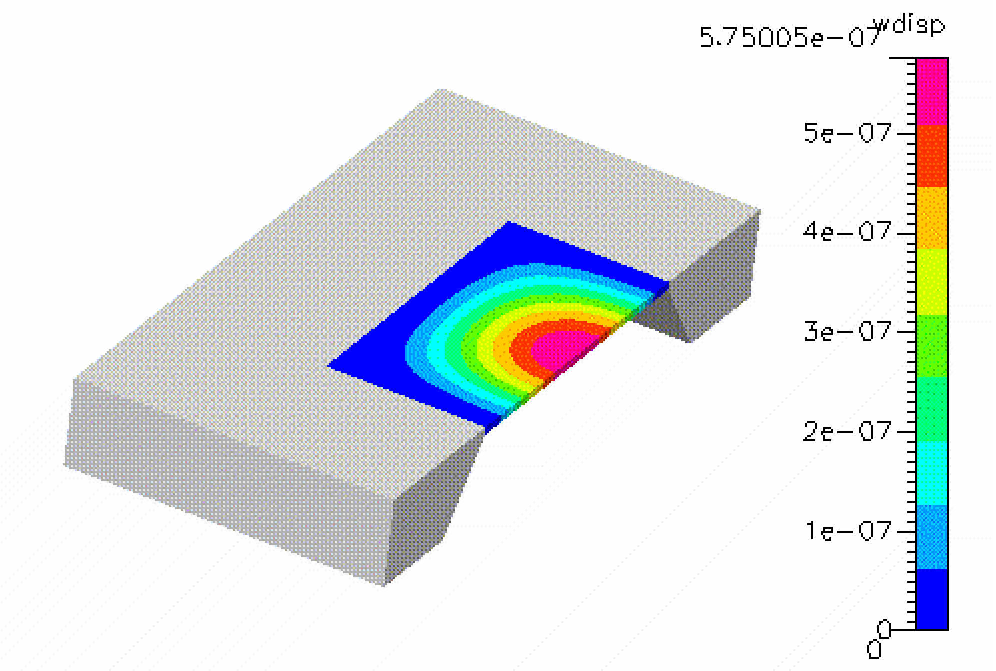
- Deflection of mechanical elements due to forces
- Stress in mechanical elements
- 3D elasticity equation, plate or beam equations
- Crystal silicon

Membrane etched in single crystal silicon:

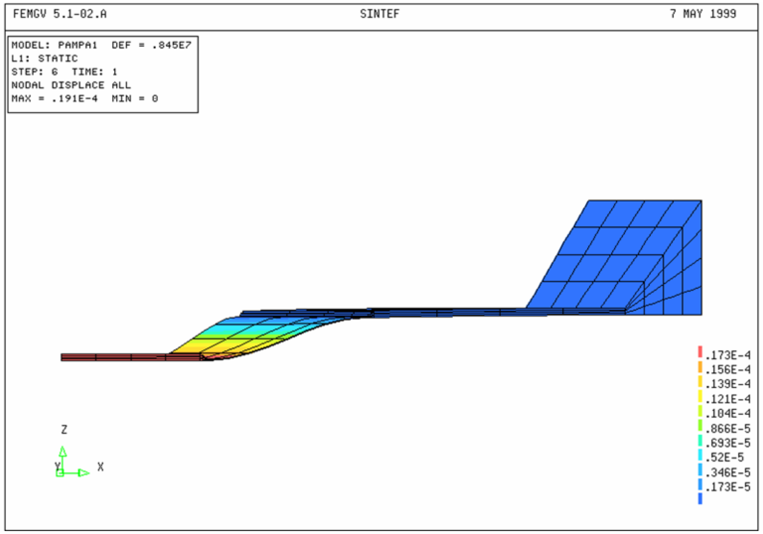
•E=1.698x10^{11} N/m^2, v=0.066

•Analytical solution Wmax=5.732 x 10^{-7}m

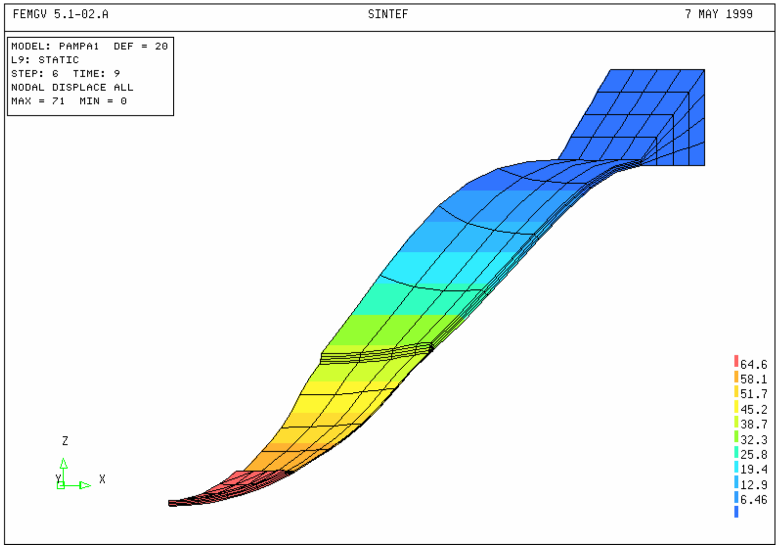
•Present prediction Wmax=5.750 x 10^{-7}m

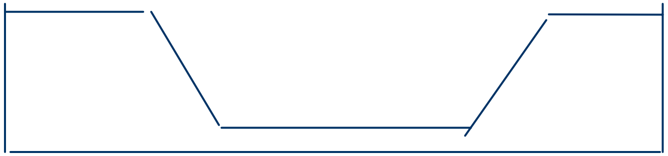


From compression to tension



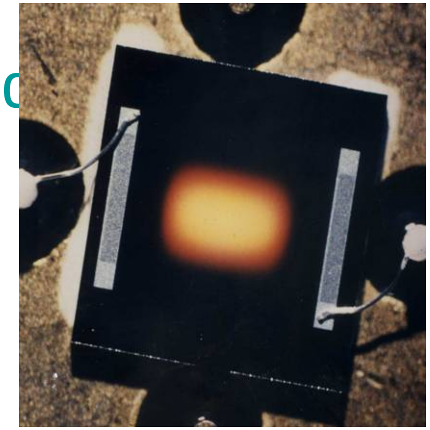
- Turn membrane upside down
- Small pressures, thin membrane bends down, compression on lower side close to edges
- Large pressures, thick membrane bends down, thin membrane in state of tension

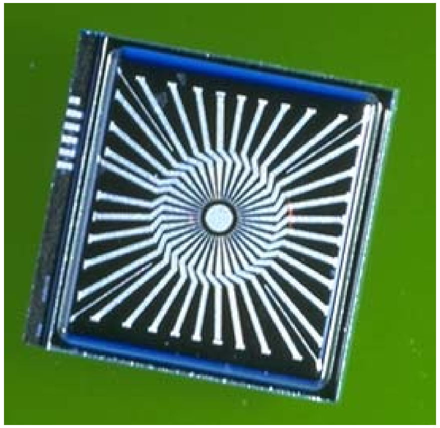


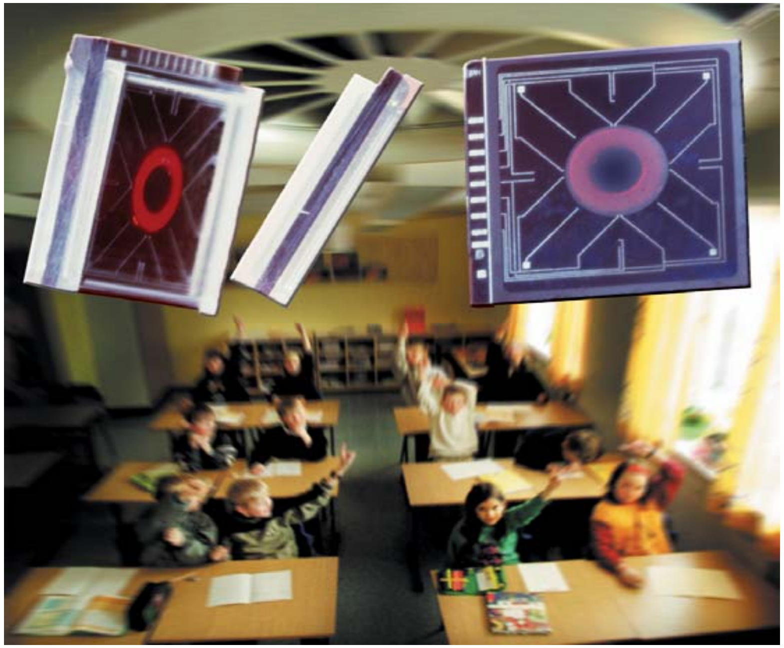


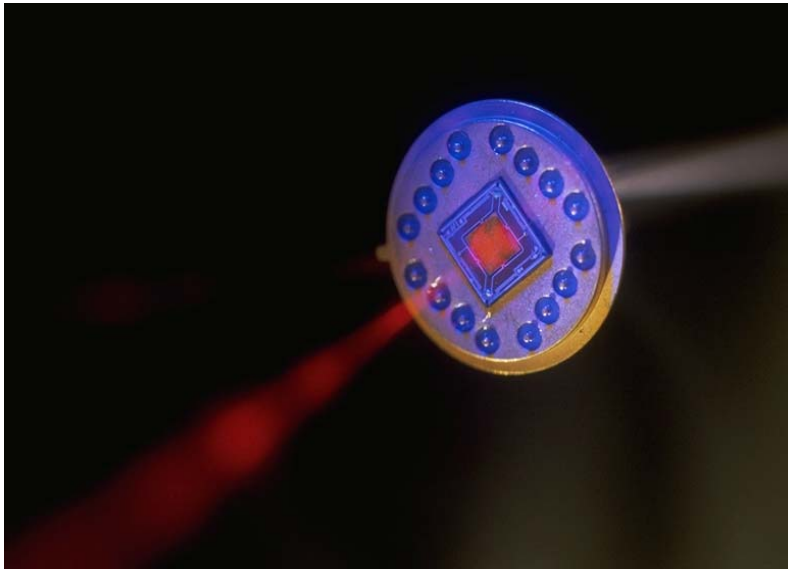
Photoacoustic gas sensor

- Combination of 3 micromachined elements, SINTEF patents
- SensoNor Microsystems Products



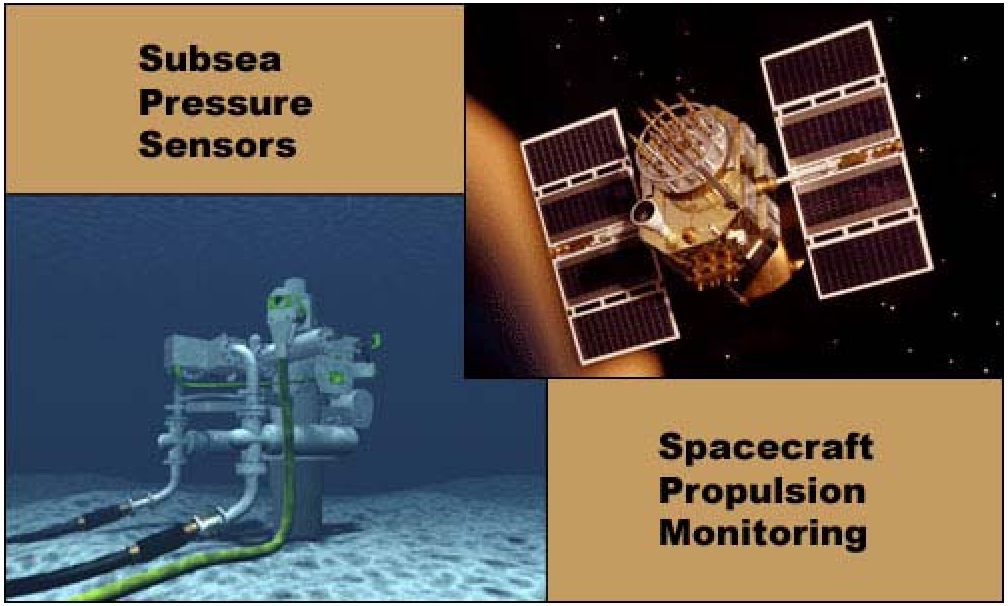


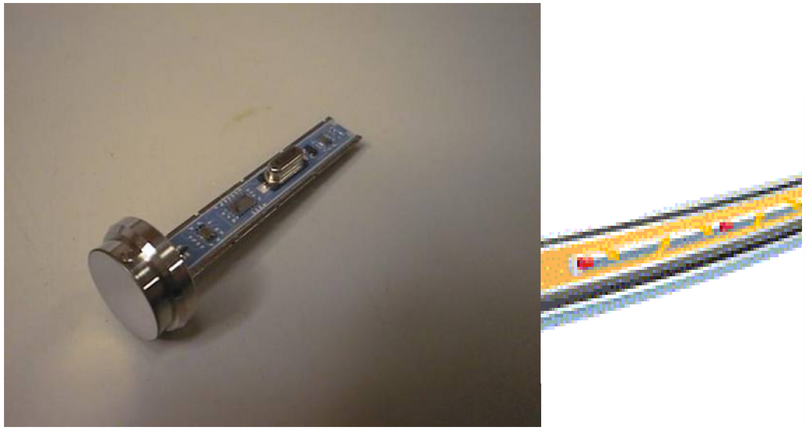




Trykksensor for høye trykk (2000 bar)

(Produseres i SINTEFs lab)





PRESENS

STATE OF THE ART SENSOR SOLUTIONS

Subsea oil well instrumentation

Flow from different zones of an oil reservoir is controlled by an integrated well control system

Requirements:

1000 bar, 180 C

Monitor

Pressure
Flow
Fluid composition
Temperature

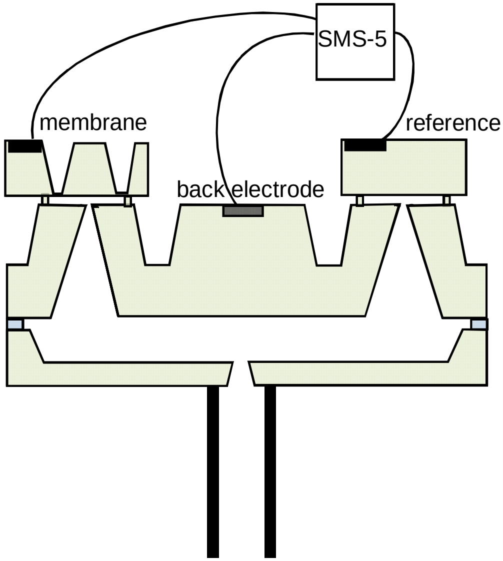
$$C = \frac{A\varepsilon\varepsilon_0}{x}$$

<u>SINTEF</u>: Interdisciplinarity!

- **Design, fabrication and testing of**
  - **entire “fish”**
  - **diff. p sensor for flow meas.**
- **Design/test of HT-ASIC electronics**

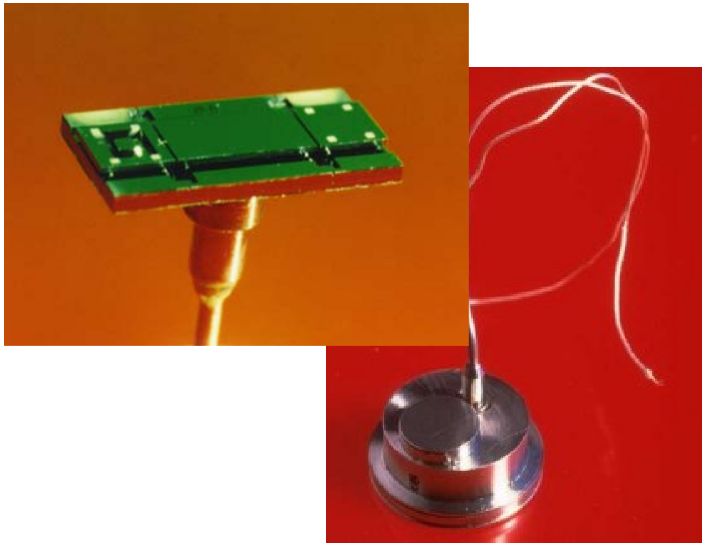
<u>PreSens</u>:

- **Absolute p sensor**

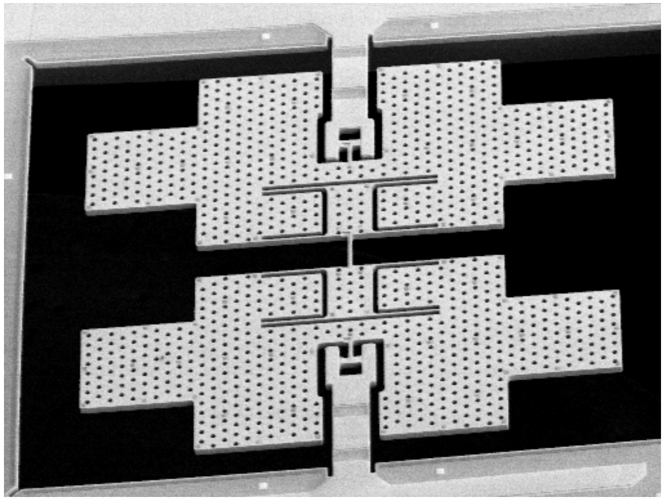


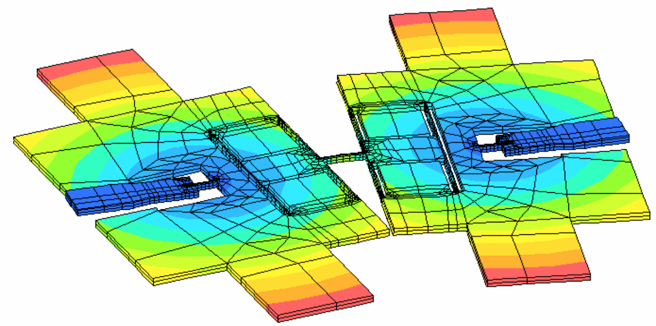
- **Capacitive sensing element**
- **3-stack fusion bonding (high-T)**

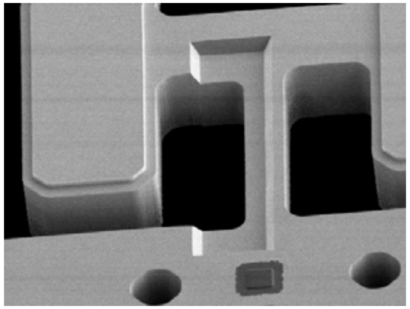
  - **Low zero shift vs. T and p**
  - **Low noise**
  - **High long term stability**

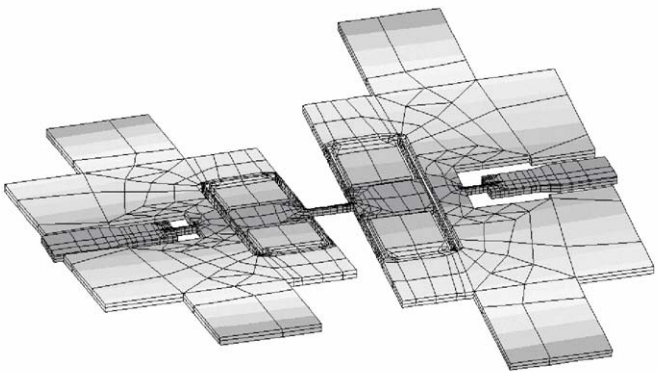


Capacitive roll-over sensor: SensoNor's SAR10

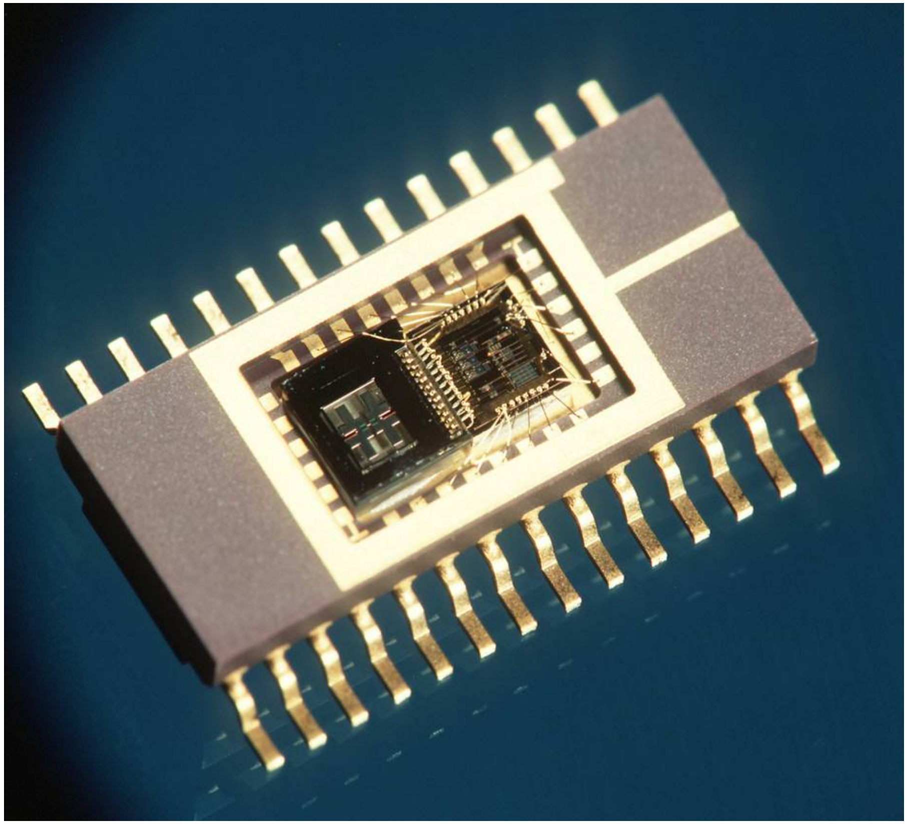








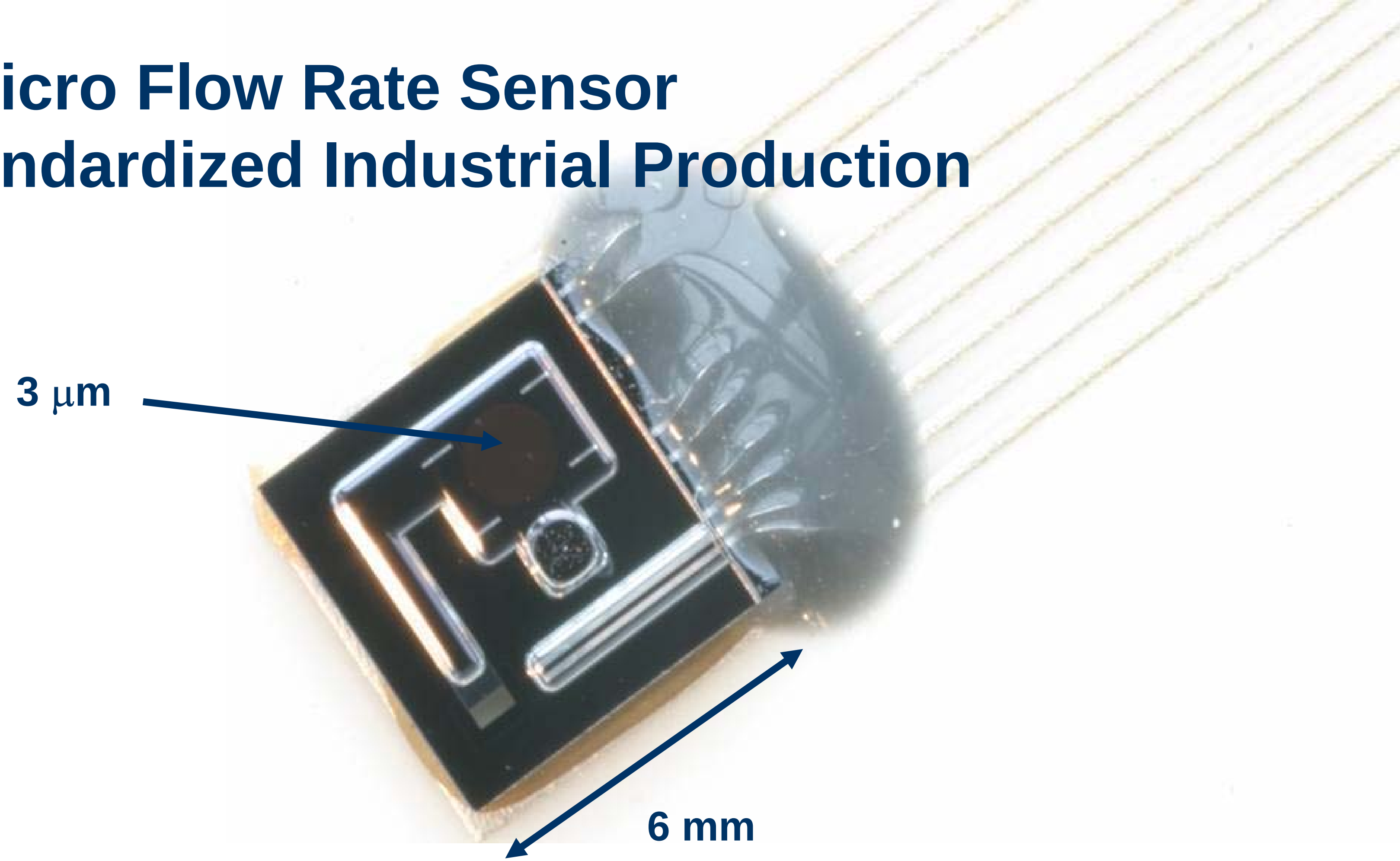
Microelement as part of an electrical circuit



- Read out
- Amplification
- Signal processing
- Feedback

- Lumped element modelling/equivalent circuits

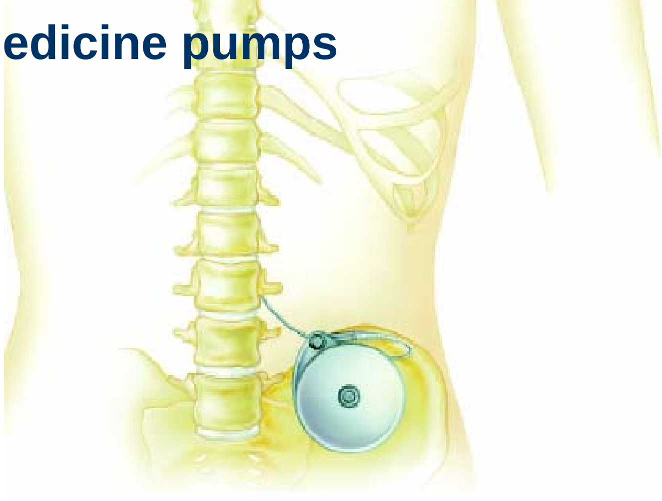
New Micro Flow Rate Sensor for Standardized Industrial Production

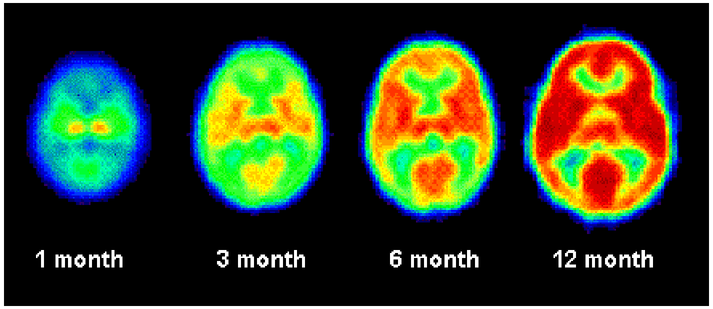


Microsystems and Nanotechnology
SINTEF Information and Communication Technology

The miniature flow rate sensor can be used in diverse applications

Safety check of implanted medicine pumps



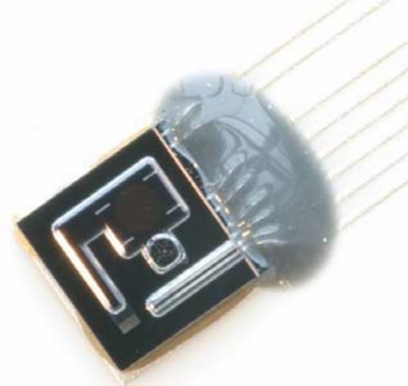


Reagent flow rates in micro reactor for PET radioactive isotopes

Measuring flow rates of enzymes into bacteria analysis chip

Monitoring the dosing of medicine

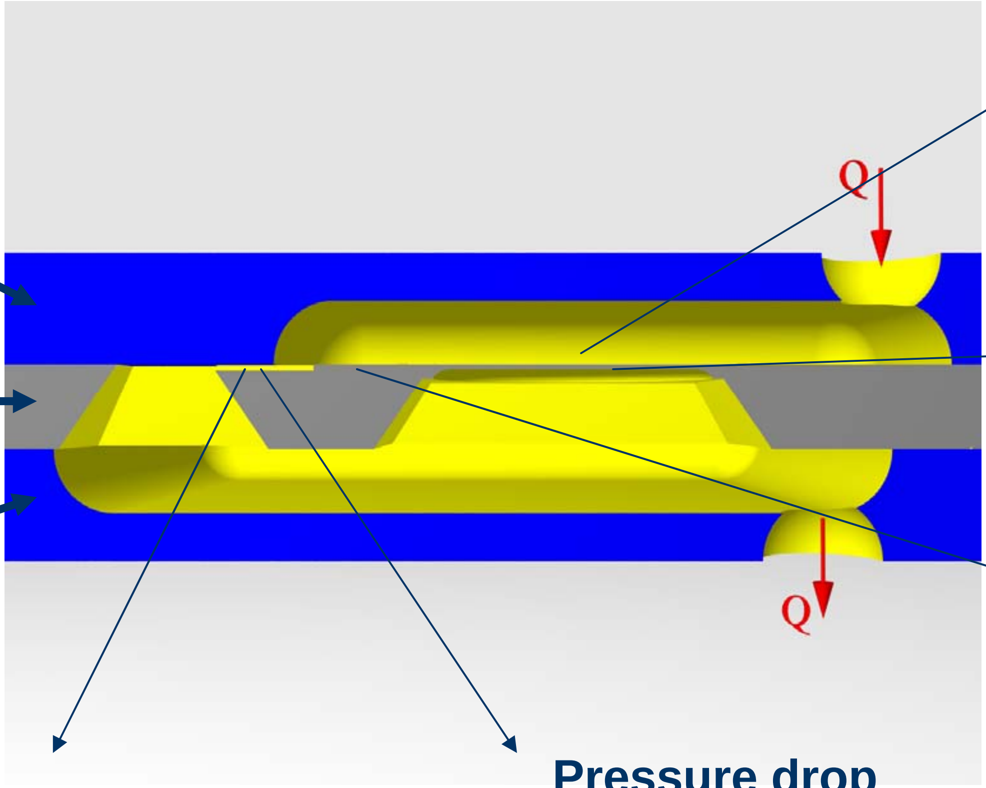
The world’s leading manufacturing line for tire sensors is used for production of the flow sensor



The SensoNor foundry produces a micro-fluidic element for the first time

An Infineon Technologies Company

The new design suggests a low-noise, mechanically robust flow sensor



Sensitive and strong membrane

Pyrex

Protected piezoresistors for stress measurements

Silicon

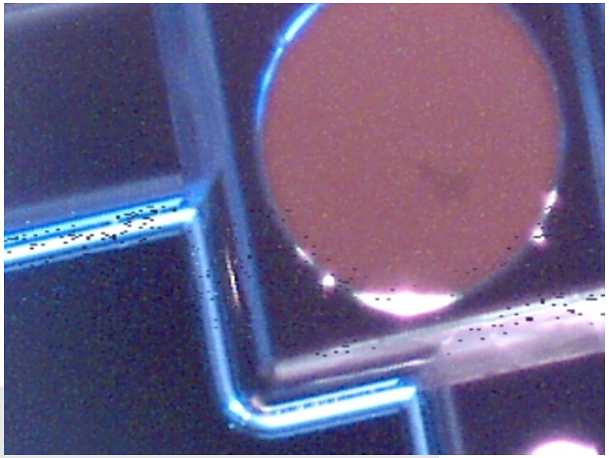
Pyrex

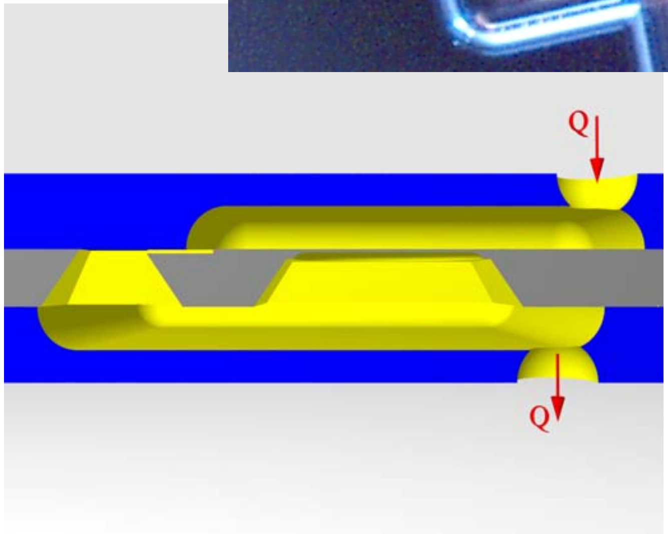
Temperature sensing diode

Channel depth 11 μm

Pressure drop proportional to the flow rate

Volum-strømningsmåler

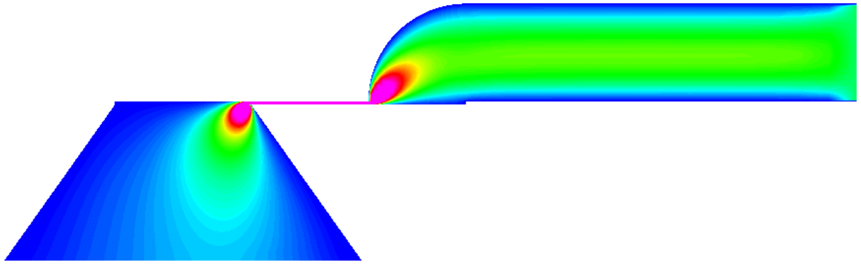




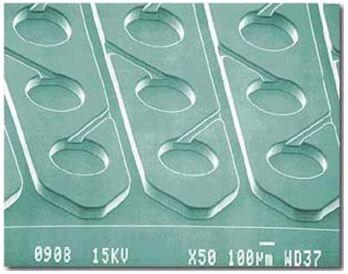
- Applikasjoner: Dosering, tilføring av reagenter, måle flow gjennom analysesystem
- Væskestrøm gjennom brikken
- Glass-silisium-glass brikke
- Laminær strøm, lave Re tall
- Differensiell trykksensor (membran + piezomotstander)
- Trang kanal med trykkfall, Pouseille strøm
- Trykkfall ~ 100 -200 Pa
- Integrert temperaturmåler

- Kanal: 800x1500x10 μm
- Flow rate 2 μl/min

$$\Delta p = \frac{12 \cdot \eta \cdot l \cdot Q}{w \cdot h^3}$$



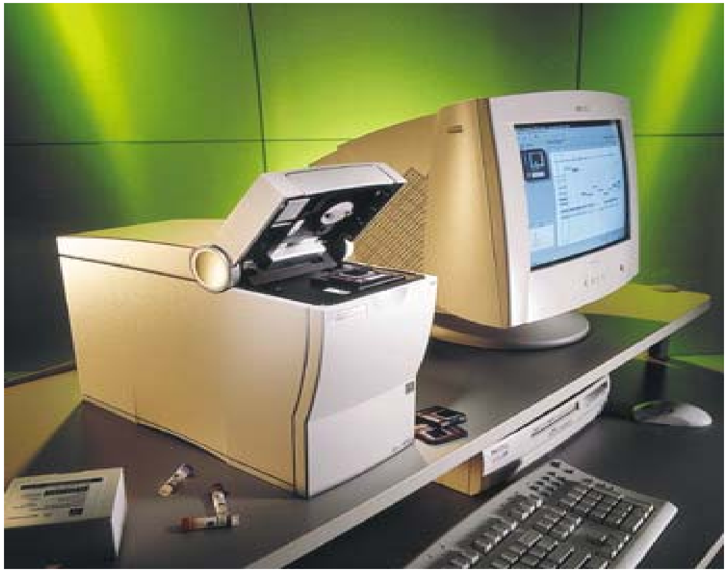
Micro-channels



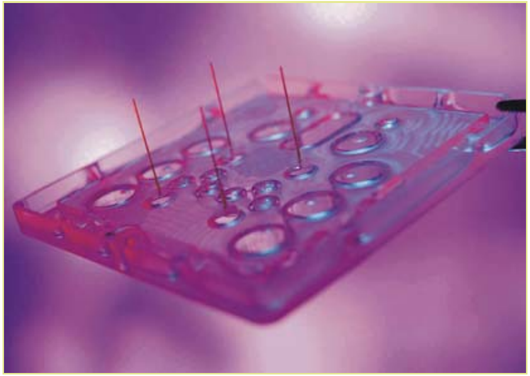
- Kanaler med vertikale vegger i silisium

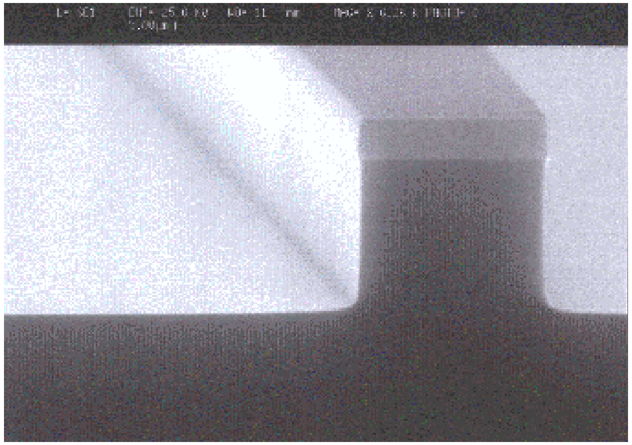
- Sprøytestøping av plast

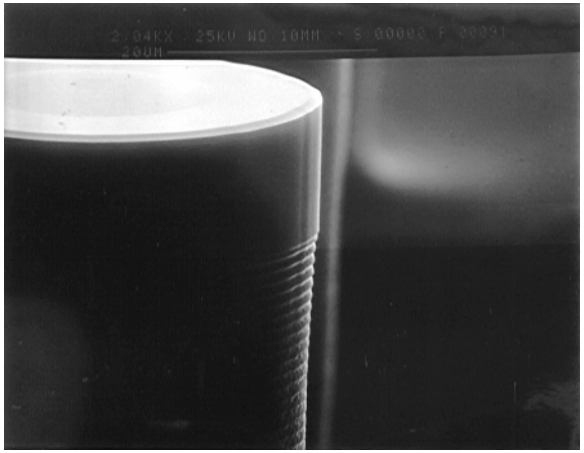
  Støpeformene generert f.eks. via silisium + elektropletering



Caliper



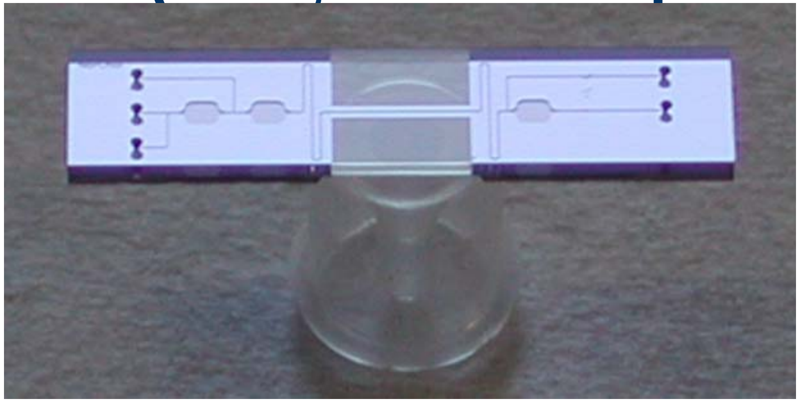




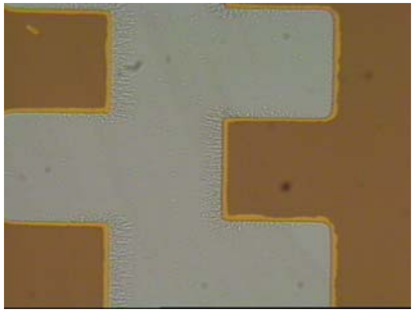
New:
Deep reactive ion etch DRIE,
BOSCH process

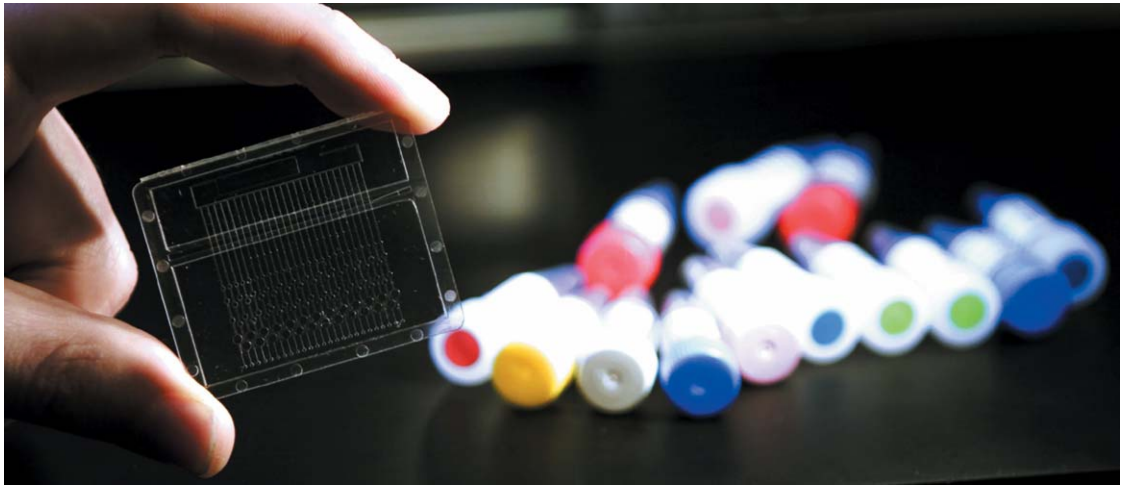
Lab-on-a-chip: NorChip's μ-TAS DNA/RNA/protein analyse

Oppkonsentrering av kliniske prøver
Filtrering til rent materiale(RNA, DNA eller proteiner)
Amplifisering
Optisk deteksjon

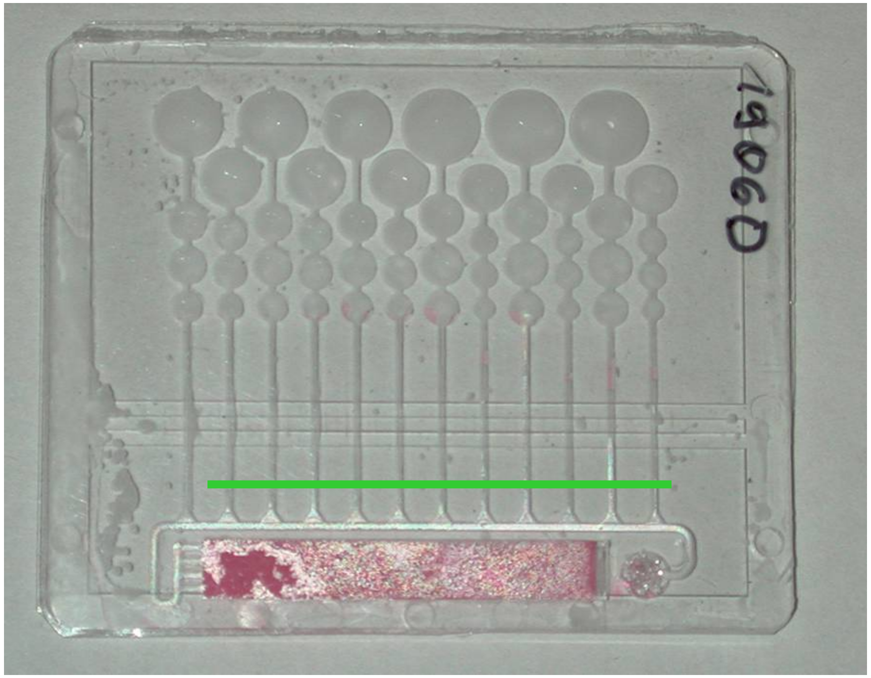


NORCHIP





Polymer chip for amplification / optical detection



- Injection moulding of COC polymer
- 75 μm thick COC membrane chemically bonded with bicyclohexyl
- Channels coated with PEG to prevent adsorption of target and enzymes
- Produced by IMM, Germany

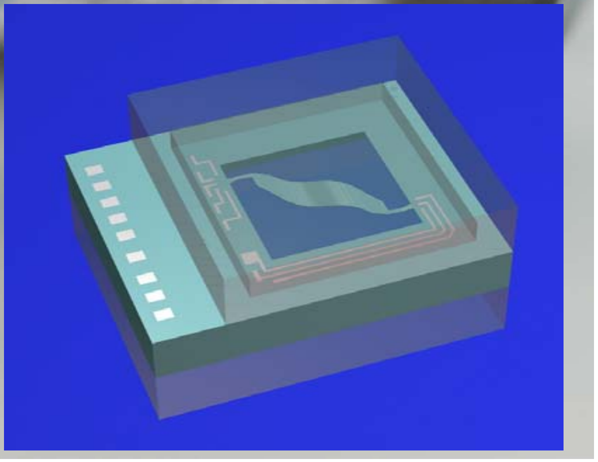
- **Dimensions: 40 x 50 x 2 mm**
- **12 channels with cross section 400 x 150 μm**

- **50 nl fluid plugs in each channel**
- **Amplification of different parts of RNA in each channel**

Surface modification

- Hydrophilic / hydrophobic surfaces
- Lithographic patterning
- E.g. deposition of self-assembled -monolayers

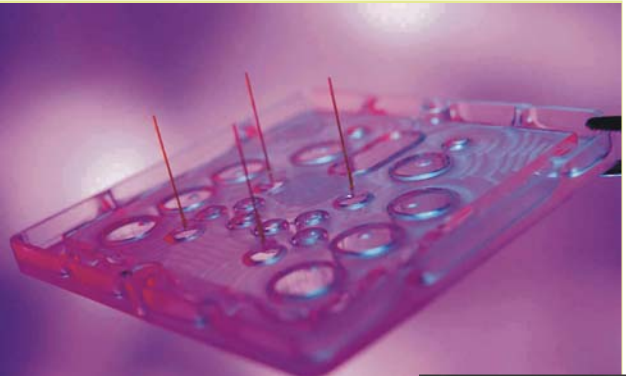
- Chemically active surfaces
- Biotechnologically active surfaces



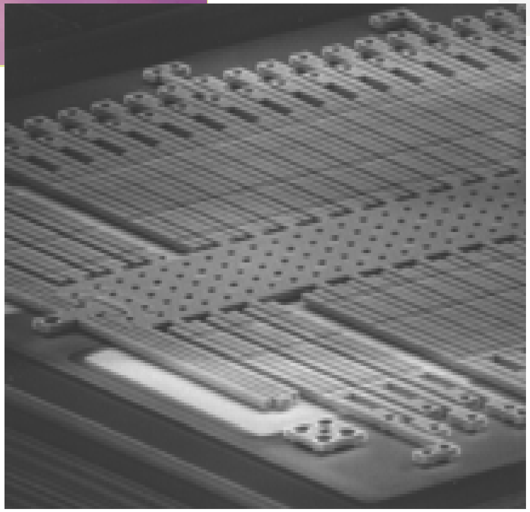
- Resonance shift due to attached molecules
- E.g. thermal actuation of resonance vibrations

Course contents, 4 main “cases”:

1) Micro fabrication
2) Design of lithographic masks
3) Physics governing behaviour of microsystems
4) Modelling of behaviour of microsystems

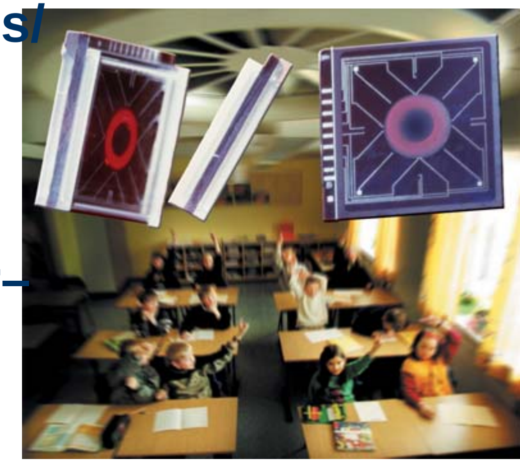


PCR analysis – microfluidics



Accelerometer – Inertial forces

Projector – optics/mechanics/ electrostatic



Pressure sensor– elasticity/ electronics

- Oppgave:

Finn mikro-foundrier på web

Søk på f.eks.
microtechnology
foundry
mpw
mumps
multi user
micromachining